

A Defect Model of Reliability

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Outline

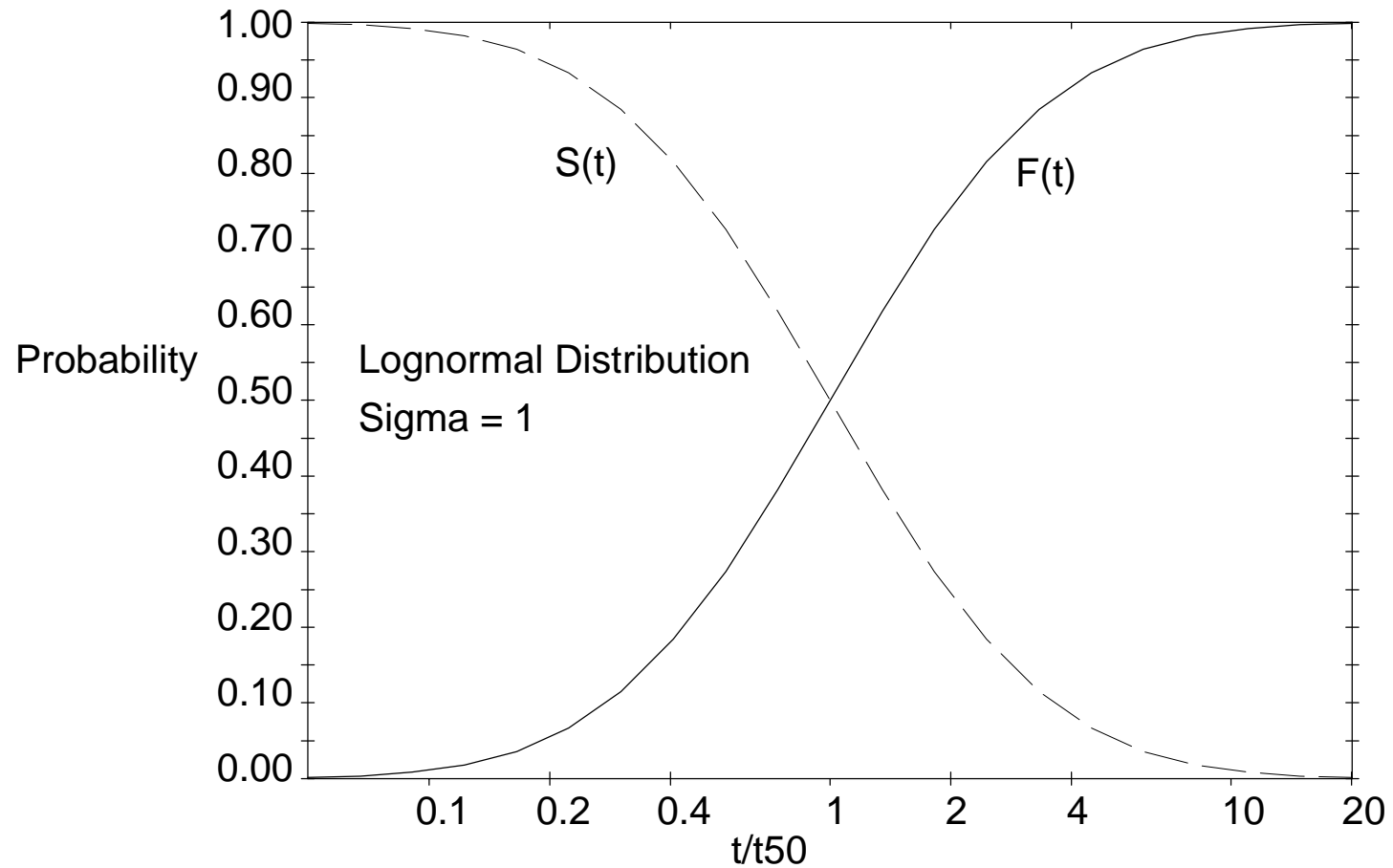
- Reliability Statistics
- Defect Reliability
 - Relationship between yield and reliability
- Accelerated Stressing and Burn-In
- Analysis of Reliability Data
 - Test Flows
 - Model Extraction
- Reliability Prediction
 - Effect of Die Area
 - Effect of Defect Density
 - Effect of Burn In
 - Standard Reliability Indicators

Reliability Statistics

- Several mathematical functions are used to describe the evolution of a population.
- Cumulative distribution function $F(t)$:
 - Probability that a unit from original population fails by time t
 - $F(t=0) = 0$, $F(t=\text{infinity}) = 1$, $F(t)$ increases monotonically, $F(t)$ undefined for $t < 0$. $0 < F(t) < 1$.
- Survival function $S(t) = 1 - F(t)$:
 - Probability that a unit from original population survives to time t .
 - $S(t=0) = 1$, $S(t=\text{infinity}) = 0$, $S(t)$ decreases monotonically, $S(t)$ undefined for $t < 0$. $0 < S(t) < 1$.

Reliability Statistics

Cumulative Distribution Function and Survival Function



Reliability Statistics

- Probability density function, $f(t)$

$$f(t) = \frac{\text{Number of failures in } dt}{dt} \times \frac{1}{\text{Initial Population}}$$

$$f(t) = \frac{dF(t)}{dt} = -\frac{dS(t)}{dt}$$

$$F(t) = \int_0^t f(t) dt$$

– Of theoretical interest only.

Reliability Statistics

- Instantaneous Failure Rate, $h(t)$

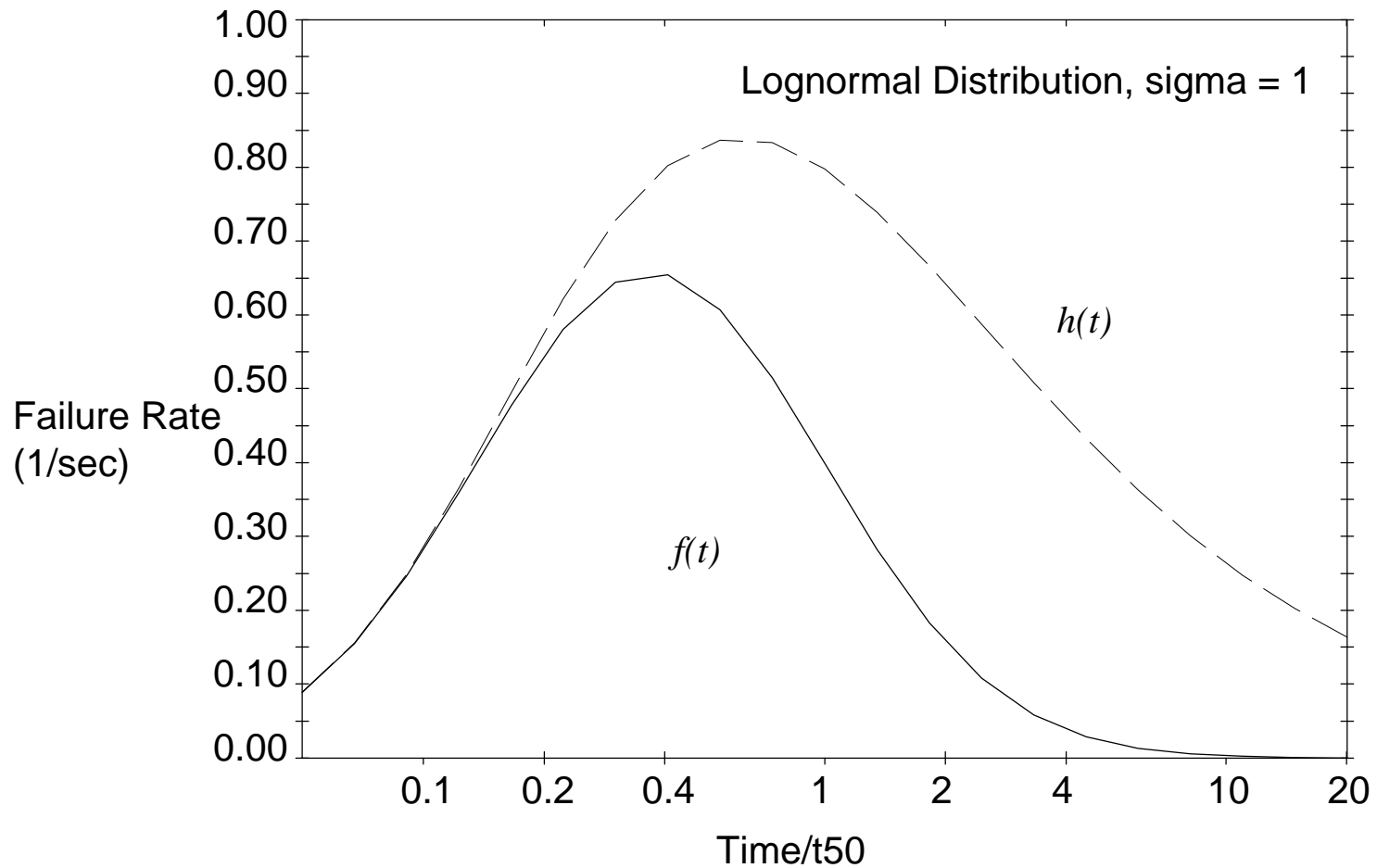
$$h(t) = \frac{\text{Number of failures in } dt}{dt} \times \frac{1}{\text{Population at time } t}$$

$$h(t) = \frac{f(t)}{S(t)} = -\frac{1}{S(t)} \frac{dS(t)}{dt} = -\frac{d \ln S(t)}{dt}$$

- $h(t)$ can increase or decrease and have any positive value, that is, $h(t) > 0$.

Reliability Statistics

Probability Density Function $f(t)$, and Instantaneous Failure Rate $h(t)$



Reliability Statistics

- Cumulative Hazard Function, $H(t)$
- Defined by

$$H(t) = \int_0^t h(t) dt$$

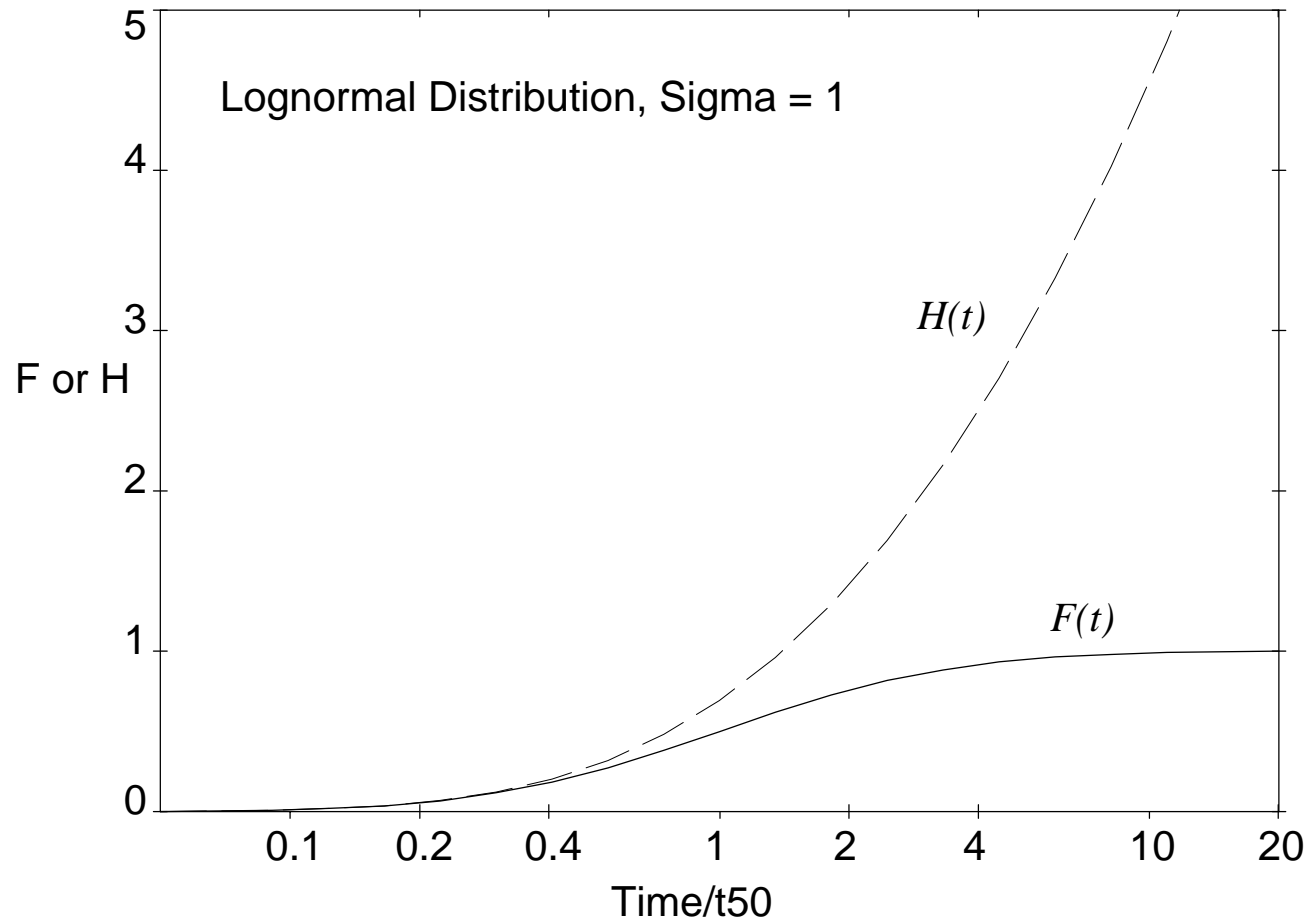
$$S(t) = \exp[-H(t)]$$

$$F(t) = 1 - \exp[-H(t)]$$

- $H(t)$ is dimensionless, like a probability, but can have any positive value.
- $H(t)$ increases monotonically with time.
- $H(t)$ is useful in analysis of “censored” data in which removals or multiple failure mechanisms occur.

Reliability Statistics

Cumulative Hazard, $H(t)$, and Cumulative Distribution Function, $F(t)$



Reliability Statistics

- The functions $F(t)$, $S(t)$, $f(t)$, $h(t)$, $H(t)$ are all interrelated. Given one, the others can be derived.
- No assumptions about the specific distribution (Weibull, Lognormal, etc. have been made).
- A program for extracting models from censored data is
 - Plot $H(t)$ from censored data
 - Determine $F(t)$ via $F(t) = 1 - \exp[-H(t)]$
 - Fit parametric distribution to $F(t)$
 - Use parametric $S(t) = 1 - F(t)$ to calculate predictions.

Reliability Statistics

- Average Failure Rates: A common reliability indicator
 - The average failure rate between times t_1 and t_2

$$\begin{aligned} \text{AFR}(t_1, t_2) &= \frac{\int_{t_1}^{t_2} h(t) dt}{t_1 - t_2} = \frac{H(t_1) - H(t_2)}{t_1 - t_2} \\ &= \frac{\ln S(t_1) - \ln S(t_2)}{t_1 - t_2} \end{aligned}$$

- For t_1 and t_2 in hours, multiply AFR by 10^9 to get units of Fits.
- For t_1 and t_2 in hours, multiply AFR by 10^5 to get units of %/1khr.

Reliability Statistics

- Cumulative Fraction Failed: Another indicator

- Fraction failing between t_1 and t_2

$$\text{Cum Fail} = F(t_2) - F(t_1) = S(t_1) - S(t_2)$$

- If $t_1 = 0$ then

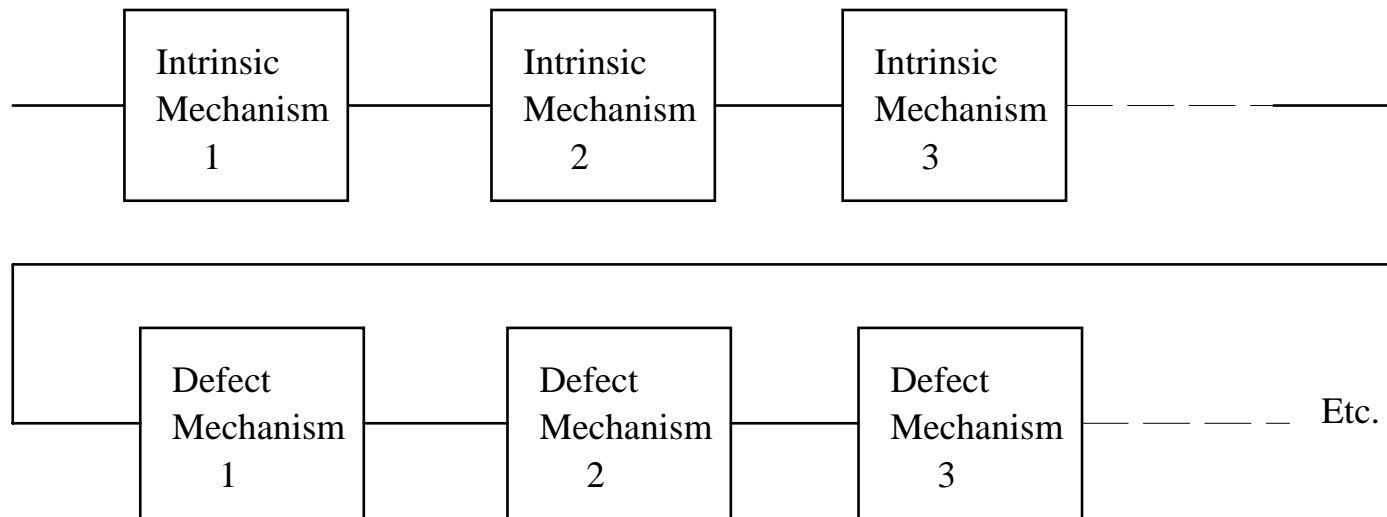
$$\text{Cum Fail} = F(t_2) = 1 - S(t_2)$$

- Multiply Cum Fail by 10^6 to get DPM (Defects per Million)

- All indicators can be expressed in terms of the Survival Function.

Reliability Statistics

- Multiple failure mechanisms
 - If the earliest occurrence of a mechanism is fatal, then the device is logically a chain:



- This is the usual case for semiconductor components. That is, there is no *functional* redundancy.

Reliability Statistics

- Multiple failure mechanisms (cont.)
 - The survival probability for a chain is the product of the survival probabilities of the links:

$$S(t) = S_{\text{mech } 1}(t) \times S_{\text{mech } 2}(t) \times \dots$$

$$= \prod_{\text{mech } i} \exp[-H_i(t)] = \prod_{\text{mech } i} \exp[-\int_0^t h_i(t') dt']$$

$$= \exp[-\int_0^t \sum_i h_i(t') dt'] \equiv \exp[-\int_0^t h(t') dt'] \equiv \exp[-H(t)]$$

- All that means is that the total instantaneous failure rate is the sum of instantaneous failure rates for each mechanism.

$$h(t) = \sum_{\text{mechanisms } i} h(t_i)$$

Intrinsic versus Defect Mechanisms

- Intrinsic mechanisms are due to non-defect-related manufacturing or design errors.
 - Typically associated with gross areas of the wafer.
- The total survival function may be written

$$S(t) = S_{\text{intrinsic mech 1}}(t) \times S_{\text{intrinsic mech 2}}(t) \times \dots \\ \times S_{\text{defect mech 1}}(t) \times S_{\text{defect mech 2}}(t) \times \dots$$

- The focus in this tutorial is on defect-related mechanisms.
 - These are the main concern in the manufacturing environment.

Defect Reliability

- Factory production reliability issues are dominated by *defects*.
- The same kinds of defects that degrade yield, degrade reliability.
 - Yield is measured before any stress: At “Sort” (wafer-level functional test) and pre-burn-in class test.
 - Reliability is measured by post-burn-in class test.
- Since the “yield” and “reliability” defects are from the same source, yield and defect reliability are related.
- Yield is routinely measured - it can be used to predict reliability.
- Yield fallout is easier to measure than reliability fallout: It is larger.

Defect Size Distribution

- Establish distribution by visual counting and classifying particles and other defects in the factory.
- $D(x)$ is the *observed* number of defects per unit area with dimension (eg. diameter) between x and $x+dx$

- For example, Stapper's model*

$$D(x) = \bar{D} \times (x / x_0)^2 \quad \text{for } x \leq x_0$$

$$D(x) = \bar{D} \times (x_0^2 / x^3) \quad \text{for } x > x_0$$

- x_0 is a characteristic length \ll lithographic resolving power. (Operators can't see very small defects.)
- \bar{D} is the defects per unit area of defects of all sizes.

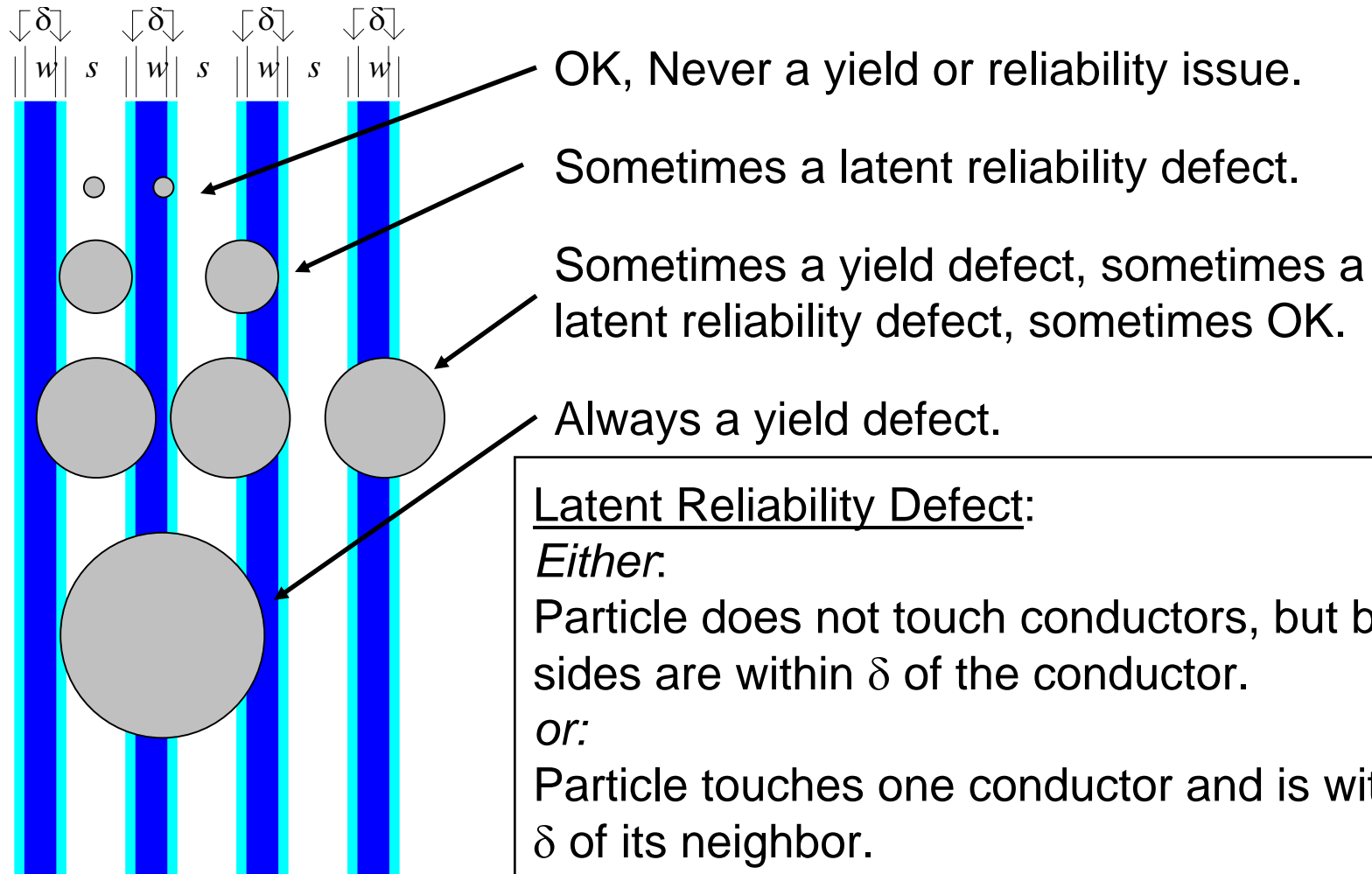
* C. H. Stapper, "Modeling of Integrated Circuit Defect Sensitivities", IBM J. Res. Develop. Vol. 27, pp 549-557 (1983)

Probability of “Yield” and “Reliability” Defects.

- “Yield” defects prevent operation of the device at before any stress ($t = 0$).
- Latent “reliability” defects will eventually kill the device (that is, at $t > 0$).
- In simple cases, the probability of occurrence of a given defect type can be *calculated* as a function of defect size, assuming random spatial distribution of defects.*
- We’ll calculate the probability of “Yield” defects and “Reliability plus Yield” defects falling on a metal comb.

* See, for example, C. H. Stapper, “Modeling of defects in integrated circuit photolithographic patterns.” IBM J. Res. Develop. Vol. 28, pp 461-475 (1984)

Probability of “Yield” and “Reliability” Defects



Probability of “Yield” and “Reliability” Defects

- Calculation of proportion of yield and reliability defects assuming random distribution of defects of diameter x .

- $P_{\text{yield}}(x)$ is the proportion of “yield” defects.

$$\begin{aligned}
 P_{\text{yield}}(x) &= 0, && \text{for } x < s \\
 &= \frac{x - s}{s + w}, && \text{for } s \leq x < 2s + w \\
 &= 1, && \text{for } x \geq 2s + w
 \end{aligned}$$

- $P_{\text{yield \& latent rel}}(x)$ is the proportion of “reliability” and “yield” defects. ($s \Rightarrow s - 2\delta$ and $w \Rightarrow w + 2\delta$)

$$\begin{aligned}
 P_{\text{yield \& latent rel}}(x) &= 0, && \text{for } x < s - 2\delta \\
 &= \frac{x - s + 2\delta}{s + w}, && \text{for } s - 2\delta \leq x < 2s + w - 2\delta \\
 &= 1, && \text{for } x \geq 2s + w - 2\delta
 \end{aligned}$$

Yield and Reliability Defect Densities

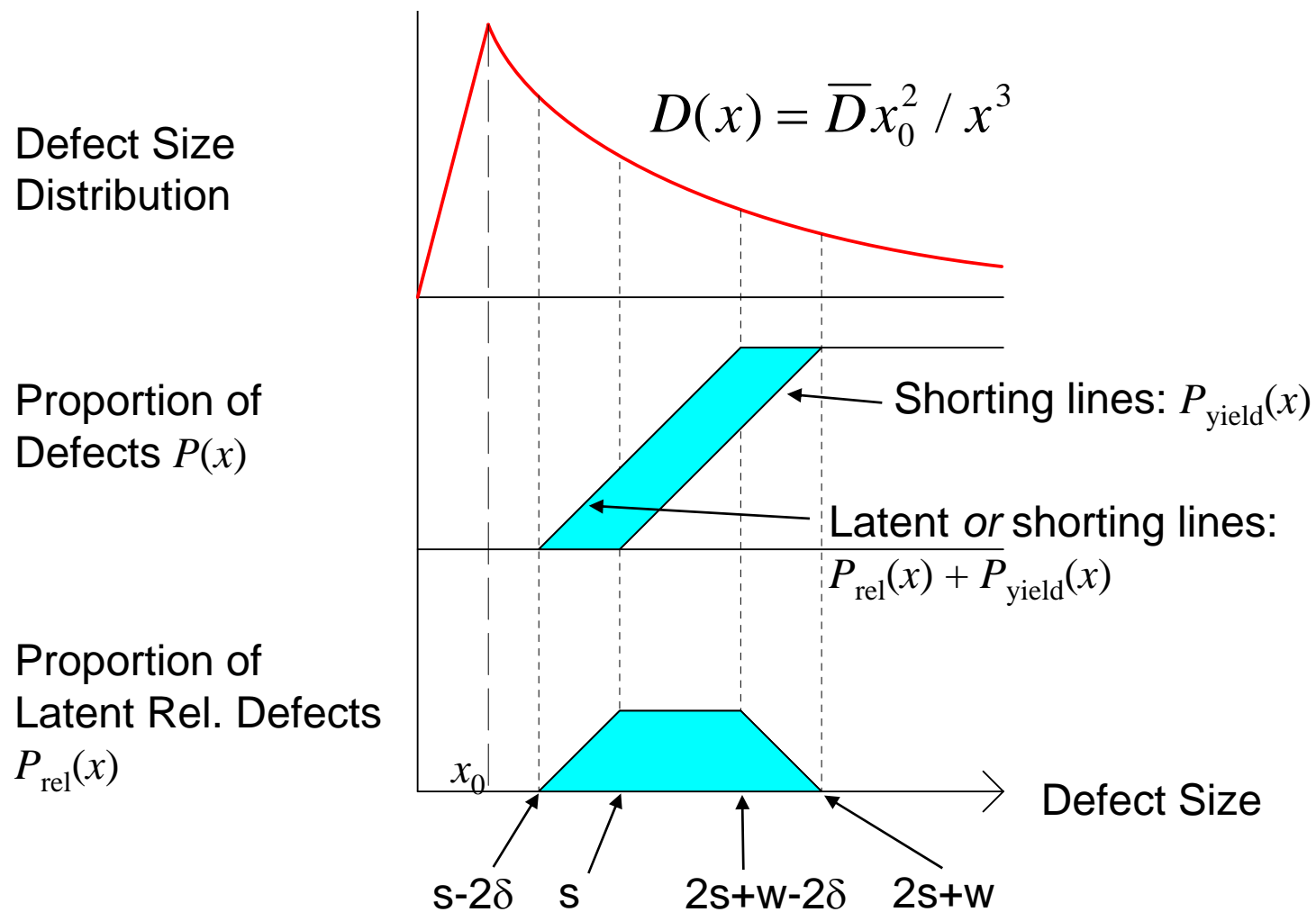
- Combine
 - Defect size distribution.
 - Probability of type of defect vs defect size.
- Calculate the defect density of defects
 - which are fatal to device at $t = 0$:

$$D_{\text{yield}} = \int_0^{\infty} D(x) P_{\text{yield}}(x) dx = \frac{\bar{D}x_0}{2s(w + 2s)}$$

- and those which are latent reliability defects:

$$D_{\text{rel}} = \int_0^{\infty} D(x) P_{\text{rel}}(x) dx = \frac{\bar{D}x_0}{2} \left[\frac{1}{(s - 2\delta)(w + 2s - 2\delta)} - \frac{1}{s(w + 2s)} \right]$$

Yield and Reliability Defect Densities



Relationship Between Yield and Reliability Defect Densities

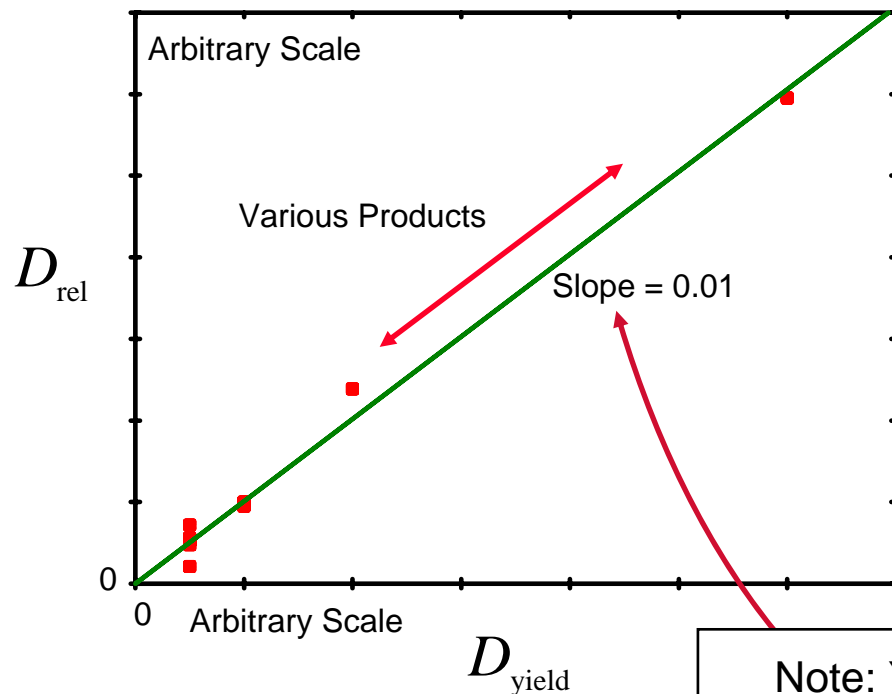
- Reliability and yield defect densities are proportional.

$$\frac{D_{\text{rel}}}{D_{\text{yield}}} = \delta \times \frac{2(w + 3s)}{s(w + 2s)} + \text{higher order terms in } \delta$$

- The ratio of latent reliability defect density to yield defect density depends on
 - The *shape* of the defect size distribution.
 - The *pattern* on which the defects fall (layout sensitivity)
 - The definition of “latency” (the value of δ).
 - An assumption of non-interacting, randomly distributed defects.

Relationship Between Yield and Reliability Defect Densities

- The ratio $D_{\text{rel}}/D_{\text{yield}}$ can be measured...



Reliability defect density as measured by 6 hour burn-in fallout, versus yield for various products.

$F(t)$ = Proportion failing at time t

$D_{\text{rel}} = -\ln\{F(t = 6 \text{ hours})\} / \text{Area}$

$D_{\text{yield}} = -\ln\{\text{Yield}\} / \text{Area}$

Note: Yield defect density is 100X larger than reliability defect density. So it's easier to measure.

Simulation of Defect Reliability

- In general, analytical calculation of reliability and yield defectivities is complex because of
 - Complex defect size distributions.
 - Non-circular defects with orientation distributions.
 - Complex substrate patterns.
- Often it is easier to use Monte Carlo methods to evaluate defectivities by *simulation*.
- We'll discuss simulation more when we look at an assembly-related example a bit later.

Relationship Between Yield and Reliability Defect Densities

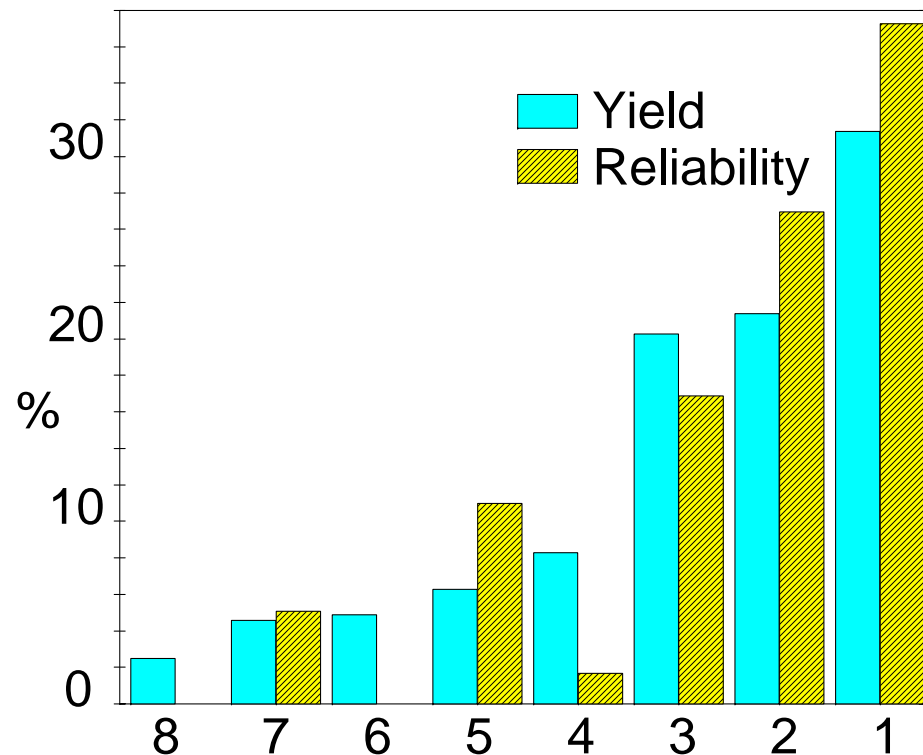
- Reliability and yield defect densities can be modeled, simulated, or measured.
- But for reliability prediction we don't care what the value of D_{rel}/D_{yield} is.
 - We only care that they proportional.
- The model we derive requires that κ_i be a constant for each mechanism and substrate pattern, i :
$$\kappa_i = \frac{D_{rel}(i)}{D_{yield}(i)}$$
- *This is not a law of nature* - it depends on a constant defect size distribution *shape*, ie. a process under statistical control.

Relationship Between Yield and Reliability Defect Densities

- Yield and reliability are proportional for all defects, especially the most frequently occurring ones.

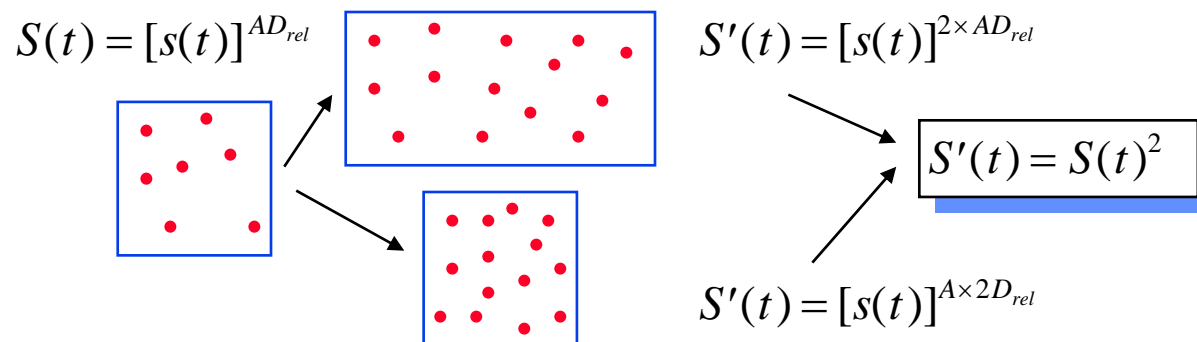
Yield and Reliability Defect Pareto

1. Metal Defects and Particles
2. W Defects and Particles
3. NVD
4. Plug Defects
5. Other Defects
6. Spacer Defects
7. Poly Defects and Particles
8. Diffusion Defects



Scaling of Defect Reliability

- Assume
 - Each defect has a survival function $s(t)$, and the density is D_{rel} (defects/cm²).
 - Random, non-interacting defects.
 - $S(t)$ is the survival probability of a die of area A .
- Consider 2 cases
 - Double the area, keep the defect density the same.
 - Double the defect density, keep the area the same.

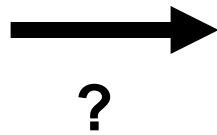


Scaling of Defect Reliability

- For one mechanism i .
- For one circuit layout pattern.
- At one condition of temperature and bias.

Case 1 (“Reference”)

$$\begin{aligned} S_i(t) &= \text{known} \\ A &= \text{known area} \\ D_{\text{rel}}(i) &= \text{“unknown”} \end{aligned}$$



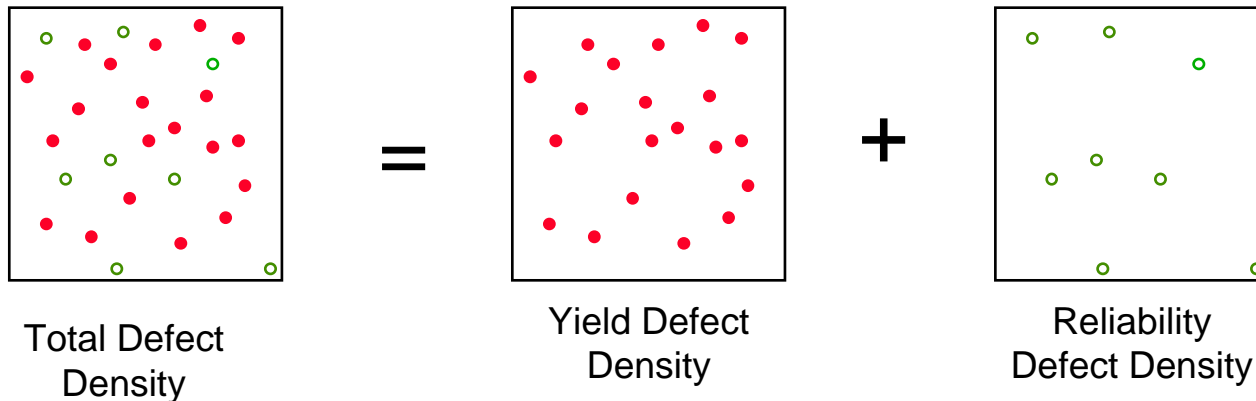
Case 2 (“Product”)

$$\begin{aligned} S'_i(t) &= \text{UNknown} \\ A' &= \text{known area} \\ D'_{\text{rel}}(i) &= \text{“unknown”} \end{aligned}$$

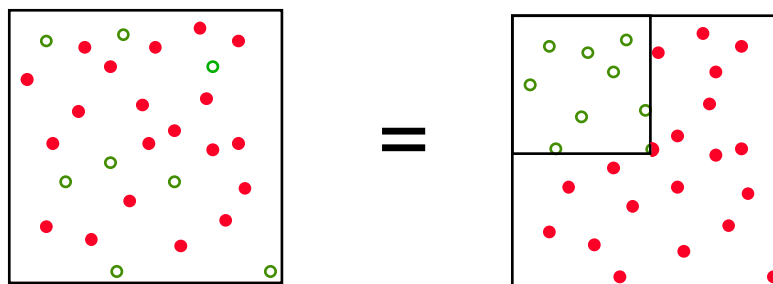
$$S'_i(t) = S_i(t) \frac{D'_{\text{rel}}(i) A'}{D_{\text{rel}}(i) A}$$

Concept of Reliability Defect Density

- Concept in this tutorial:



- Concept used in other* work:



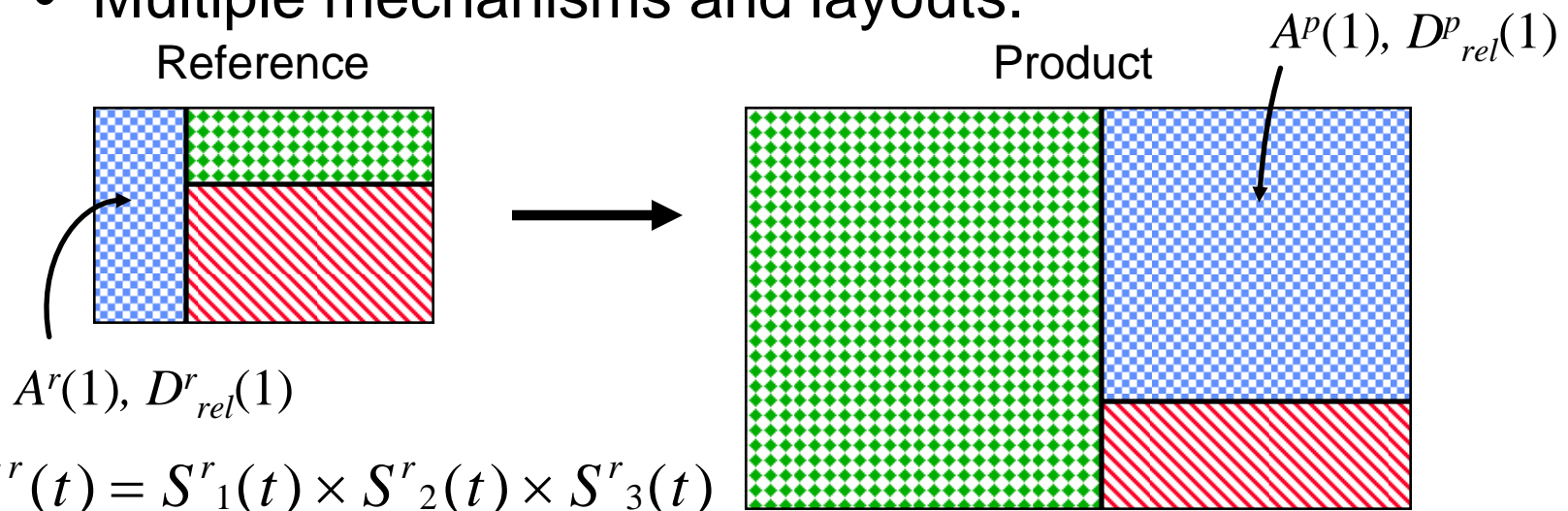
Constant defect density, “critical areas” for yield and reliability.

Problem: It’s easy to confuse physical die area (and subarea) scaling with the abstract concept of “critical area”.

* H.H. Huston, and C.P. Clarke, “Reliability Defect Detection and Screening during Processing - Theory and Implementation”, IRPS 1992, pp 268-274.

Scaling of Defect Reliability

- Consider a process reference monitor “*r*” (eg. an SRAM), and a product “*p*”.
- Multiple mechanisms and layouts.



$$S^p(t) = S^r_1(t) \frac{D^p_{rel}(1) \times A^p(1)}{D^r_{rel}(1) \times A^r(1)} \times S^r_2(t) \frac{D^p_{rel}(2) \times A^p(2)}{D^r_{rel}(2) \times A^r(2)} \times S^r_3(t) \frac{D^p_{rel}(3) \times A^p(3)}{D^r_{rel}(3) \times A^r(3)}$$

Scaling of Defect Reliability

The critical relationship...

$$\frac{D_{\text{rel}}^p(i) \times A^p(i)}{D_{\text{rel}}^r(i) \times A^r(i)} = \frac{\kappa_i(\text{product}) \times D_{\text{yield}}^p(i) \times A^p(i)}{\kappa_i(\text{reference}) \times D_{\text{yield}}^r(i) \times A^r(i)} \approx \frac{D_{\text{yield}}^p(i) \times A^p(i)}{D_{\text{yield}}^r(i) \times A^r(i)}$$

If this ratio is unity, then this is true.

The ratio is unity when the *shape* of the defect size distribution is a constant. This will be true for a process which is in statistical control.

Scaling of Defect Reliability

- Reliability defect densities, D_{rel} , are not well known and are small, but D_{yield} are related to production indicators and are larger.
- Appeal to constancy of D_{rel}/D_{yield} for each mechanism/subdie to write

$$S^P(t) \cong S_1(t)^{\frac{D^P_{yield}(1) \times A^P(1)}{D^r_{yield}(1) \times A^r(1)}} \times S_2(t)^{\frac{D^P_{yield}(2) \times A^P(2)}{D^r_{yield}(2) \times A^r(2)}} \times S_3(t)^{\frac{D^P_{yield}(3) \times A^P(3)}{D^r_{yield}(3) \times A^r(3)}}$$

- In general:

$$S^P(t) = \prod_i [S_i^r(t)]^{R_i(p|r)}$$

$$R_i(p|r) = \frac{D^P_{yield}(i) \times A^P(i)}{D^r_{yield}(i) \times A^r(i)}$$

This is not yet in a form corresponding to the usual yield statistics acquired by the factory...

Yield Statistics

- Assuming Poisson statistics, the yield for the compound die is given by

$$Y^P = Y_{\text{intrinsic}}^P \times \exp[-D_{\text{yield}}^P(1)A^P(1)] \times \exp[-D_{\text{yield}}^P(2)A^P(2)] \\ \times \exp[-D_{\text{yield}}^P(3)A^P(3)]$$

$$Y^P = Y_{\text{intrinsic}}^P \times \exp\left(\sum_j -D_{\text{yield}}^P(j)A^P(j)\right) = Y_{\text{intrinsic}}^P \times \exp(-D_{\text{yield}}^P \times A^P)$$

$$D_{\text{yield}}^P \times A^P = -\ln\left(\frac{Y^P}{Y_{\text{intrinsic}}^P}\right)$$

Subdie area-weighted
defect density.

Total die area.

$$D^P \equiv \frac{\sum_j D_{\text{yield}}^P(j)A^P(j)}{A^P} \quad A^P \equiv \sum_j A^P(j)$$

Scaling of Defect Reliability

- Some manipulation shows that

$$R_i(p|r) = \frac{D_{\text{yield}}^p(i) \times A^p(i)}{D_{\text{yield}}^r(i) \times A^r(i)} = \frac{P^p(i) \times D_{\text{yield}}^p \times A^p}{P^r(i) \times D_{\text{yield}}^r \times A^r}$$

where the Pareto (proportion of all defects attributable to mechanism i) is defined by

$$P^p(i) \equiv \frac{D_{\text{yield}}^p(i) \times A^p(i)}{\sum_j D_{\text{yield}}^p(j) \times A^p(j)}$$

- So if $Y_{\text{intrinsic}}^p = 1$ (as usual), then

$$R_i(p|r) = \frac{P^p(i) \times \ln(Y^p)}{P^r(i) \times \ln(Y^r)}$$

Scaling of Defect Reliability: Practical Formulae

- So, in terms of the usual Pareto and yield indicators acquired as factory yield indicators at sort test:

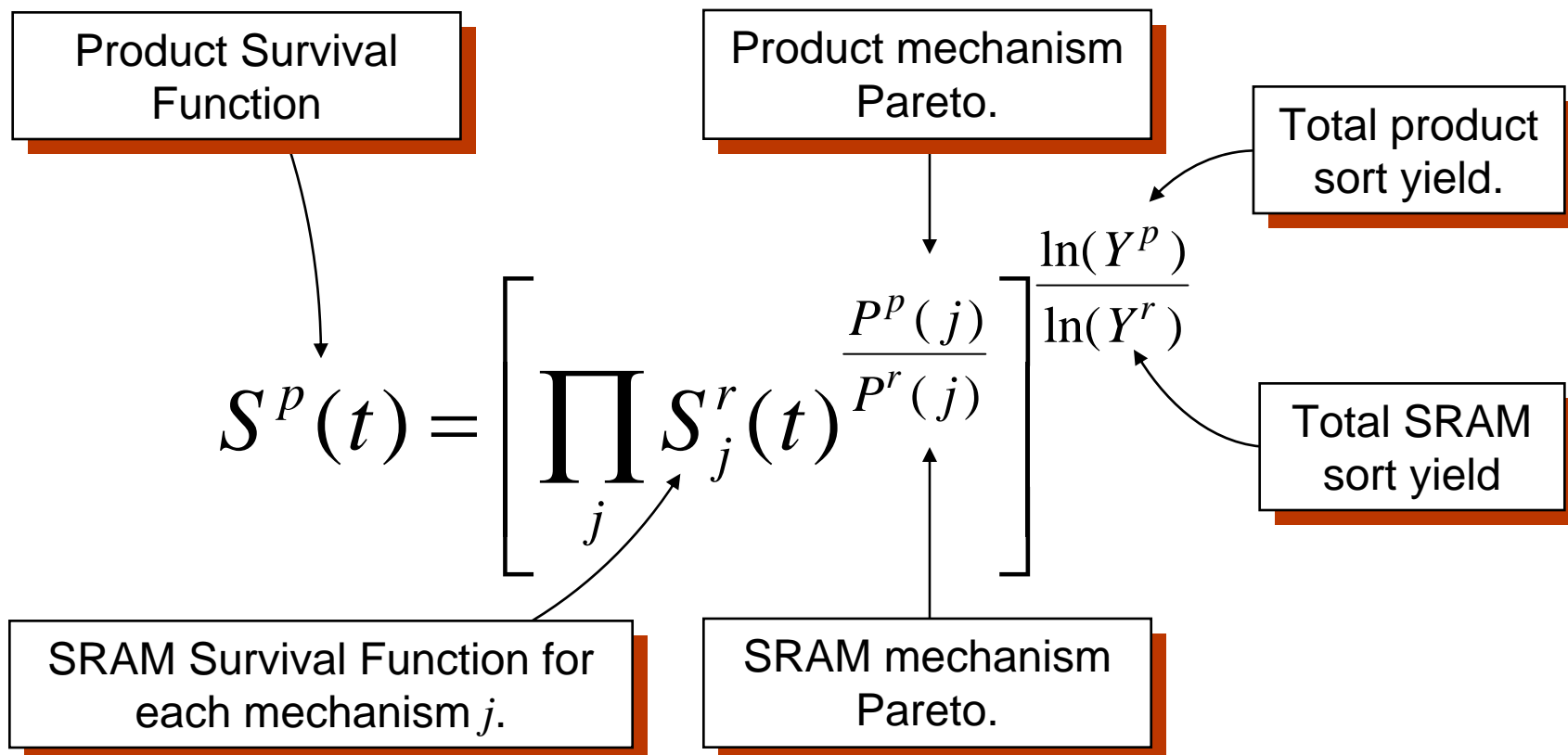
$$S^P(t) = \left[S^r_1(t)^{\frac{P^P(1)}{P^r(1)}} \times S^r_2(t)^{\frac{P^P(2)}{P^r(2)}} \times S^r_3(t)^{\frac{P^P(3)}{P^r(3)}} \right]^{\frac{\ln(Y^P)}{\ln(Y^r)}}$$

or, in general

$$S^P(t) = \left[\prod_j S^r_j(t)^{\frac{P^P(j)}{P^r(j)}} \right]^{\frac{\ln(Y^P)}{\ln(Y^r)}}$$

where we have assumed $Y^P_{intrinsic} = 1$ as is usual.

Scaling of Defect Reliability: Practical Formulae



Eg. Reference Product: SRAM. Product of Interest: Microprocessor

Scaling of Defect Reliability: Practical Formulae

- If the defect paretos are the same for reference and “unknown” product, then

$$P^p(i) = P^r(i), \quad \text{for each } i$$

so

$$S^p(t) = S^r(t)^{\frac{\ln(Y^p)}{\ln(Y^r)}}$$

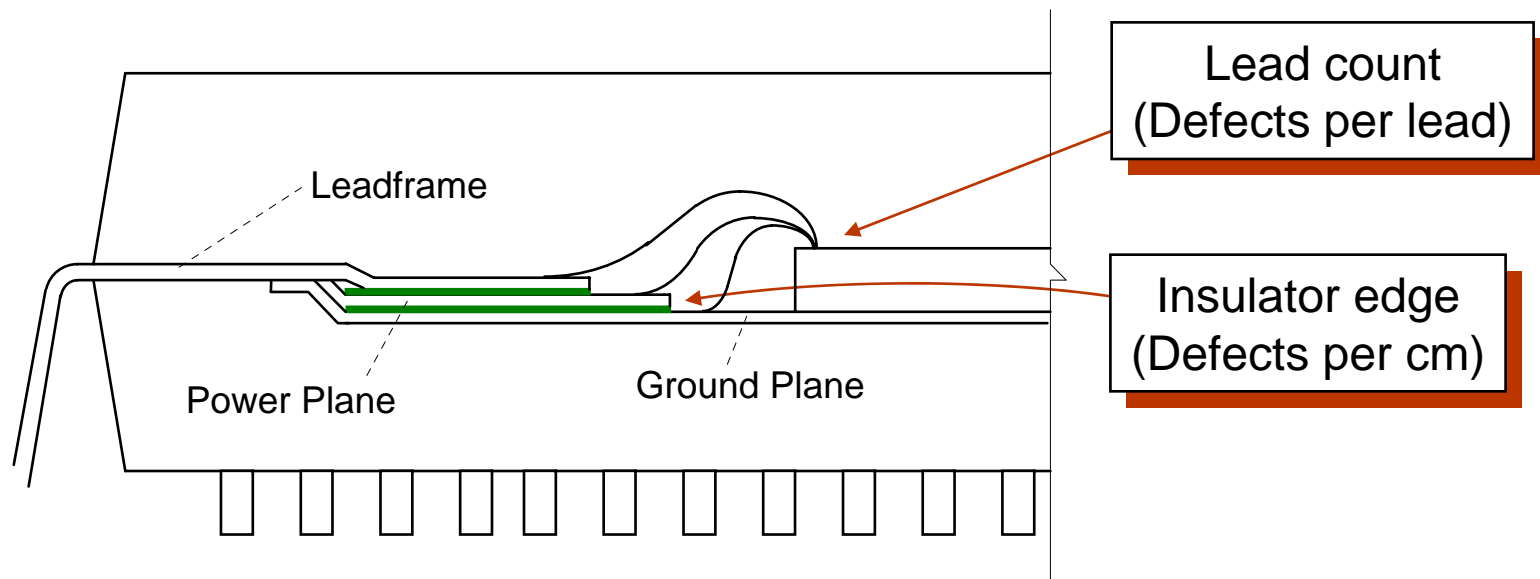
Usually a good approximation since only one or two mechanisms dominate.

where the total reference (usually SRAM) survival function is

$$S^r(t) = \prod_j S_j^r(t)$$

Extensions to Non-Die Area-Related Mechanisms

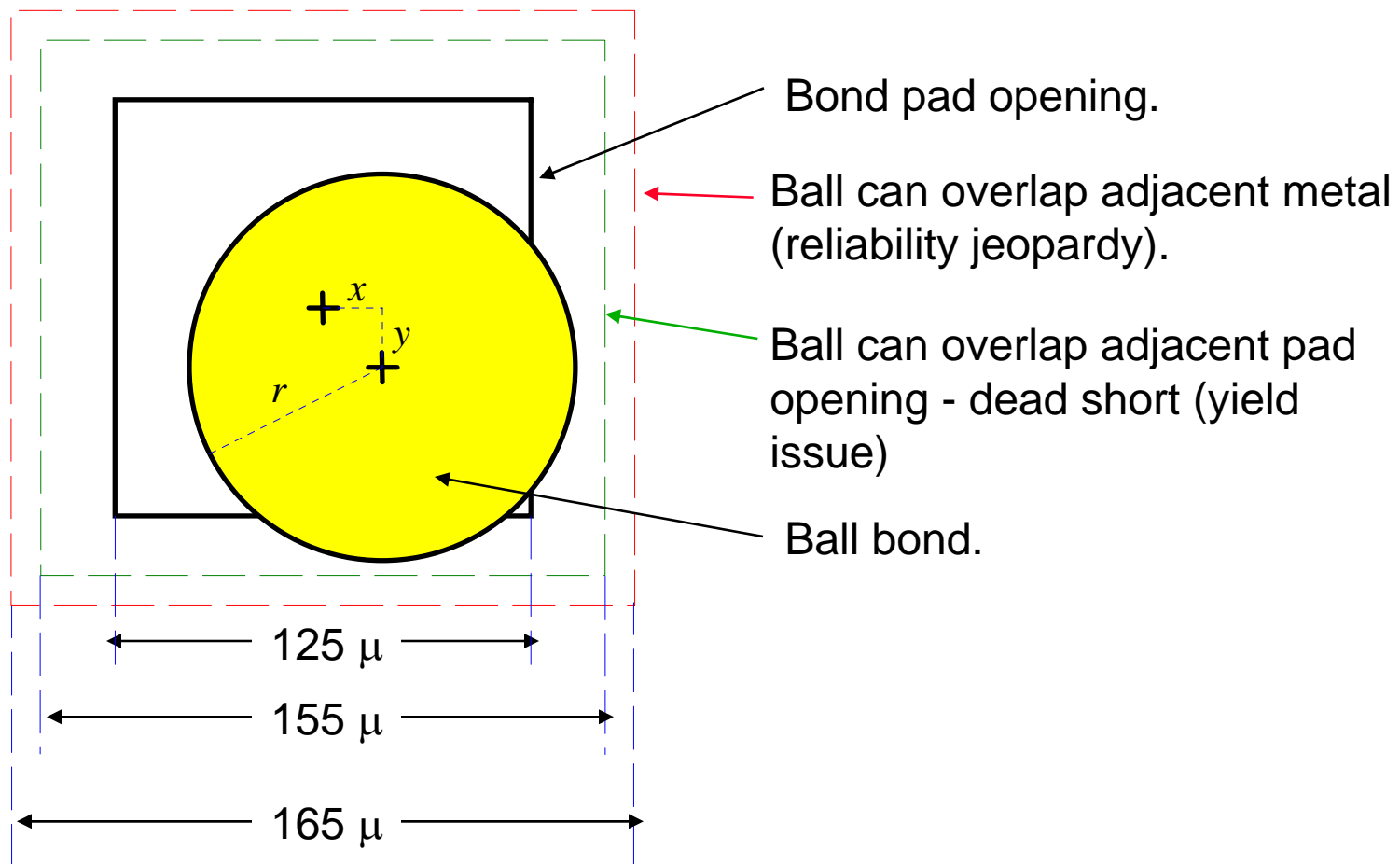
- Defect count per device may scale with other extensive properties of the product.
 - Die Area => Lead count, perimeter of dielectric edge in package, etc.
 - Areal defect density => defects per lead, defects per length of perimeter in package, etc.



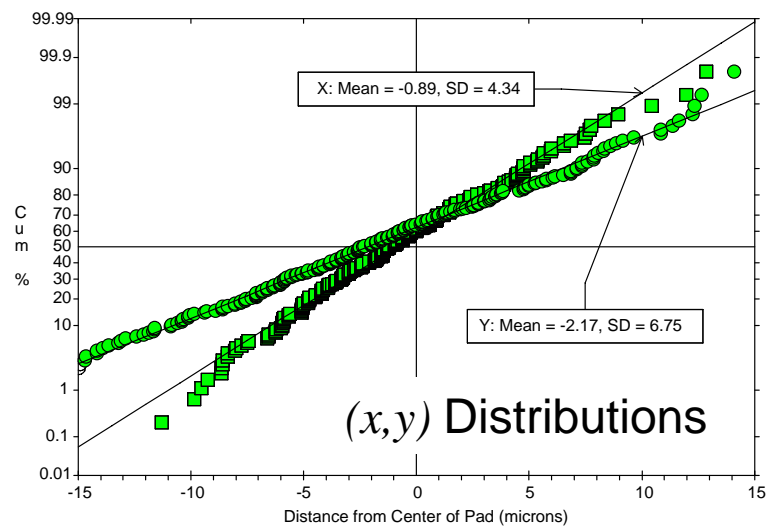
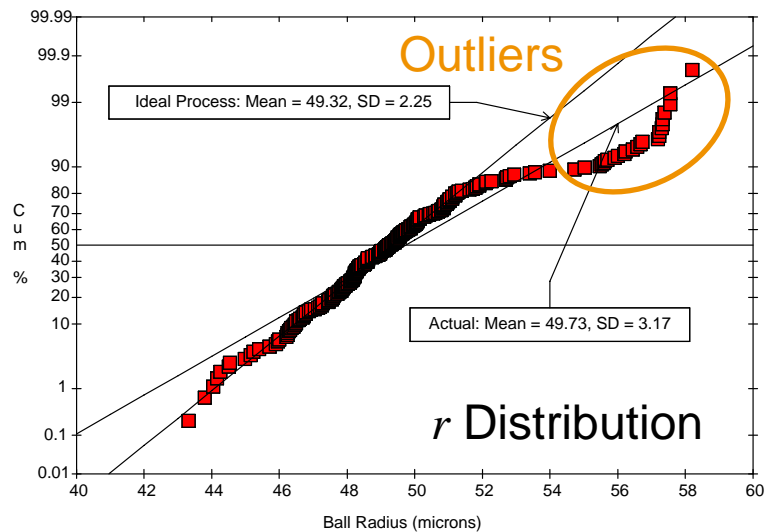
Yield/Reliability Simulation for Wire Bonding

- Measure physical process capability.
 - Make measurements of bond location and ball size.
 - Use a sample of about 200.
 - Determine distribution of bond center (x,y) , and ball diameter, r .
 - » Shape (normal, etc.), Mean, Variance.
 - » Determine whether x, y, r are correlated.
- Decide on yield and reliability specification limits.
- Calculate yield and latent reliability DPM.
 - Assume that process is in statistical control.
 - Analytical calculation - difficult, not general.
 - Simulate the process using fitted distribution parameters.

Yield/Reliability Simulation for Wire Bonding

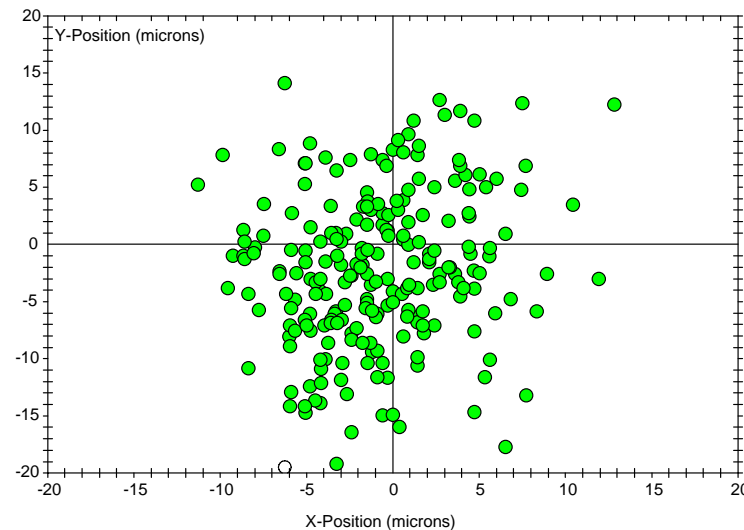


Yield/Reliability Simulation for Wire Bonding



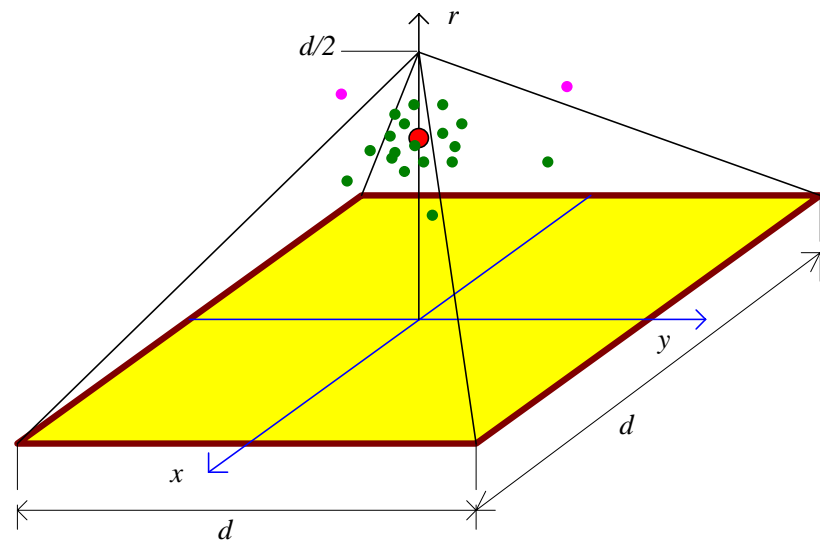
- *x*, *y*, and *r* distributions are normal and uncorrelated.
- The parameters of the process in “statistical control” are

| <i>x</i> Mean | <i>x</i> SD | <i>y</i> Mean | <i>y</i> SD | <i>r</i> Mean | <i>r</i> SD |
|---------------|-------------|---------------|-------------|---------------|-------------|
| 0 | 4.34 | 0 | 6.75 | 49.3 | 2.25 |



Yield/Reliability Simulation for Wire Bonding

- Individual bonds are points clustering around the target.
- Bonds inside pyramid pass the criterion.
- Bonds outside the pyramid fail the criterion.
- Integrate an ellipsoidal probability function centered on the target over the volume intersected by the pyramid to get DPM. *Difficult* to do in general. OR..
- Use random number generator to simulate millions of bonds using distribution parameters determined from 200-unit experiment. This is *easy!*



Yield/Reliability Simulation for Wire Bonding

Number of Bonds to Simulate

Distribution Parameters

| X-Mean | X SD | Y-Mean | Y-SD | Dia.-Mean | Dia-SD |
|--------|------|--------|------|-----------|--------|
| 0 | 4.34 | 0 | 6.75 | 98.64 | 4.5 |

Simulate Normal Deviate (mean = 0, SD = 1).
 "Numerical Recipes" by W. H. Press, B. P. Flannery, S. A. Teukolsky, W. T. Vetterling, Cambridge UP (1986), p203.

Results

| | Total Bonds | Pad Opening | Overlap Metal | Dead Short |
|-----------|-------------|-------------|---------------|------------|
| Criterion | 0 | 125 | 155 | 165 |
| Counts | 1000000 | 70232 | 68 | 3 |

```

procedure(n);
/* BONDSIM - n is the number of iterations */
{
  bnd_tbl = "@bndplacel@bond_param";
  bnd_results = "@bndplacel@bond_results";
  xmean = bnd_tbl [1, 1];
  xsd = bnd_tbl [1, 2];
  ymean = bnd_tbl [1, 3];
  ysd = bnd_tbl [1, 4];
  dmean = bnd_tbl [1, 5];
  dsd = bnd_tbl [1, 6];
  do m = 1 to n;
  {
    xcen = xmean + normdev() * xsd;
    ycen = ymean + normdev() * ysd;
    rad = 0.5 * (dmean + normdev() * dsd);
    ball_right = xcen + rad;
    ball_left = xcen - rad;
    ball_top = ycen + rad;
    ball_bott = ycen - rad;
    do p = 1 to lastcol(bnd_results );
    {
      lright = ball_right > 0.5 * bnd_results [1, p];
      lleft = ball_left < - 0.5 * bnd_results [1, p];
      ltop = ball_top > 0.5 * bnd_results [1, p];
      lbott = ball_bott < - 0.5 * bnd_results [1, p];
      lfail = lright OR lleft OR ltop OR lbott;
      if lfail then
        bnd_results [2, p] = bnd_results [2, p] + 1;
    }
  }
}
    
```

“Reliability”
 “Yield”

Scaling of Defect Reliability: Summary

- Yield and reliability defect densities may be calculated, simulated, or measured, but...
- The model requires an assumption (or null hypothesis) of
 - Random, non interacting defects.
 - An invariant *ratio* of Yield to Reliability defect densities.
- The defect-related part of the survival function scales with the density of latent reliability defects and die (or affected subdie) area.
- By hypothesis, yield and reliability defect densities are proportional, so the defect part of the survival function ALSO scales with yield defect density.
- The “practical” form of the model involves sort yield and sort Pareto data. Simplification obtains if yield defect Paretos are invariant.

Accelerated Stressing And Burn-In

- What is an acceleration factor?
 - Start with the same population
 - Case 1: Temperature T_1 , voltage V_1 , time interval dt_1 , a *certain proportion* fails.
 - Case 2: Temperature T_2 , voltage V_2 , it takes dt_2 for the *same proportion* of the population to fail.
 - The acceleration of case 2 relative to case 1, for mechanism i is

$$\frac{dt_1}{dt_2} = AF_i(2|1) \quad (\text{instantaneous})$$

$$t_1 = AF_i(2|1)t_2 \quad (\text{constant acceleration})$$

Accelerated Stressing and Burn-In

- The survival function for mechanism i at environmental condition 2 is related to the survival function at environmental condition 1 by:

$$S_i(2|t) = S_i\{1|AF_i(2|1)t\}$$

- We'll use an acceleration factor function given by:

$$AF_i(2|1) = \exp\left\{\frac{Q_i}{k}\left[\frac{1}{T_1} - \frac{1}{T_2}\right] + C_i(V_2 - V_1)\right\}$$

Accelerated Stressing and Burn-In

- For all mechanisms, the survival probability of an unknown product p at T_2 and V_2 may be calculated from the mechanism survival probabilities of a “known” reference product r at T_1 and V_1 :

$$S^p(2|t) = \prod_i [S_i^r \{1|AF_i(2|1)t\}]^{R_i(p|r)}$$

$$R_i(p|r) = \frac{D_{\text{yield}}^p(i) \times A^p(i)}{D_{\text{yield}}^r(i) \times A^r(i)} = \frac{P^p(i) \times \ln(Y^p)}{P^r(i) \times \ln(Y^r)}$$

Accelerated Stressing and Burn-In

- Consider a device undergoing t_B hours of burn-in at environmental condition “B”, followed by t hours of “use” at environmental condition “2”.

Probability of surviving t_B hours of burn-in at condition “B” AND t hours of use at condition “2”

= Probability of surviving t_B hours of burn-in at condition “B”

X **Probability of surviving t hours of use at condition “2” GIVEN THAT the device has survived t_B hours of burn-in at condition “B”.**

or, symbolically

$$\tilde{S}^p = S^p(B|t) \times S'^p(2|t)$$

so

$$S'^p(2|t) = \frac{\tilde{S}^p}{S^p(B|t)}$$

This is what the end-user sees.

Accelerated Stressing and Burn-In

- Effect of Burn-in
 - The proportion of the initial population which survives burn-in for time t_B at T_B and V_B is

$$S^P(B|t_B) = \prod_i [S_i^r \{1| AF_i(B|1)t_B\}]^{R_i(p|r)}$$

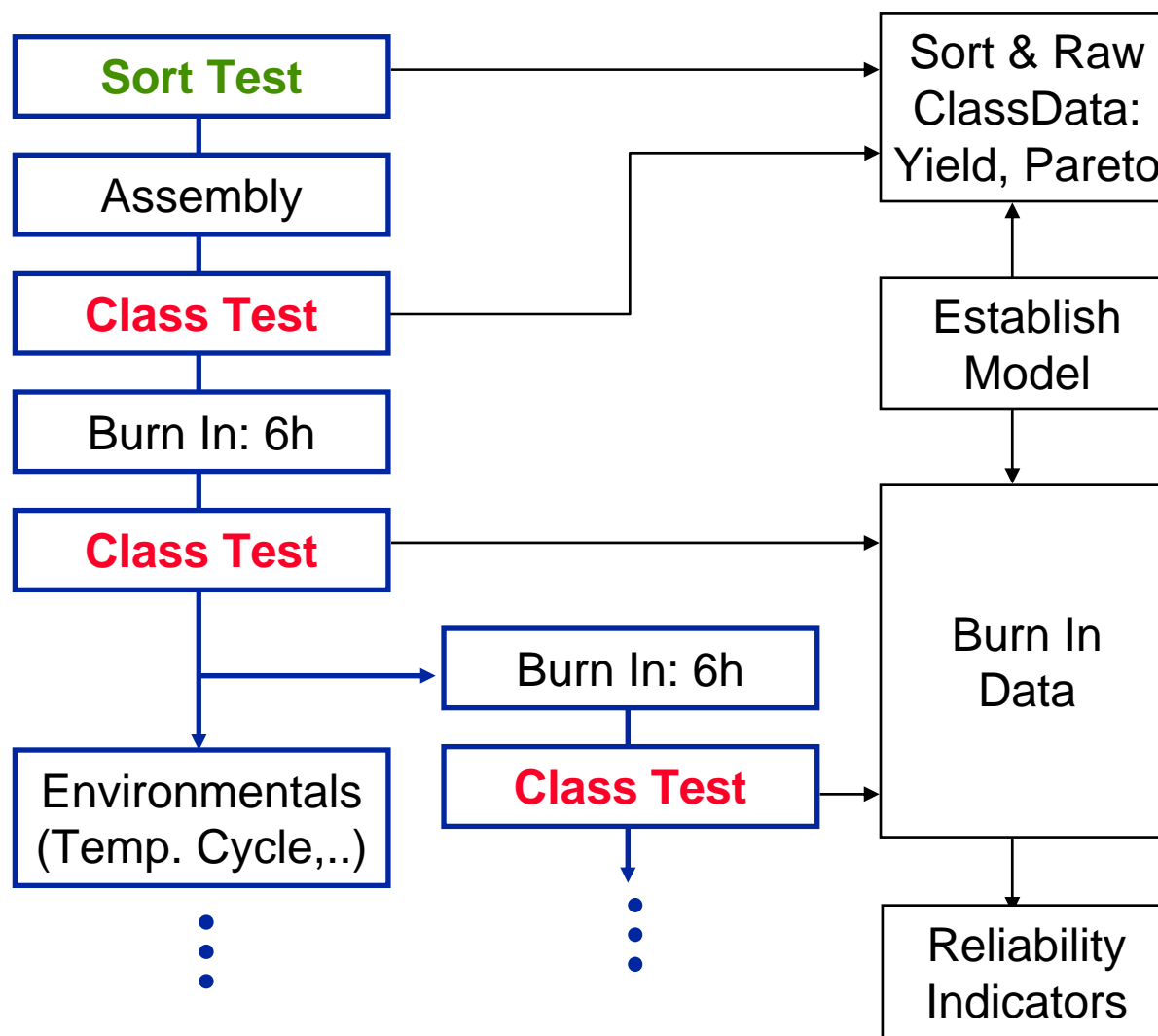
- after additional time t at T_2 and V_2 the proportion surviving is

$$\tilde{S}^P = \prod_i [S_i^r \{1| AF_i(2|1)t + AF_i(B|1)t_B\}]^{R_i(p|r)}$$

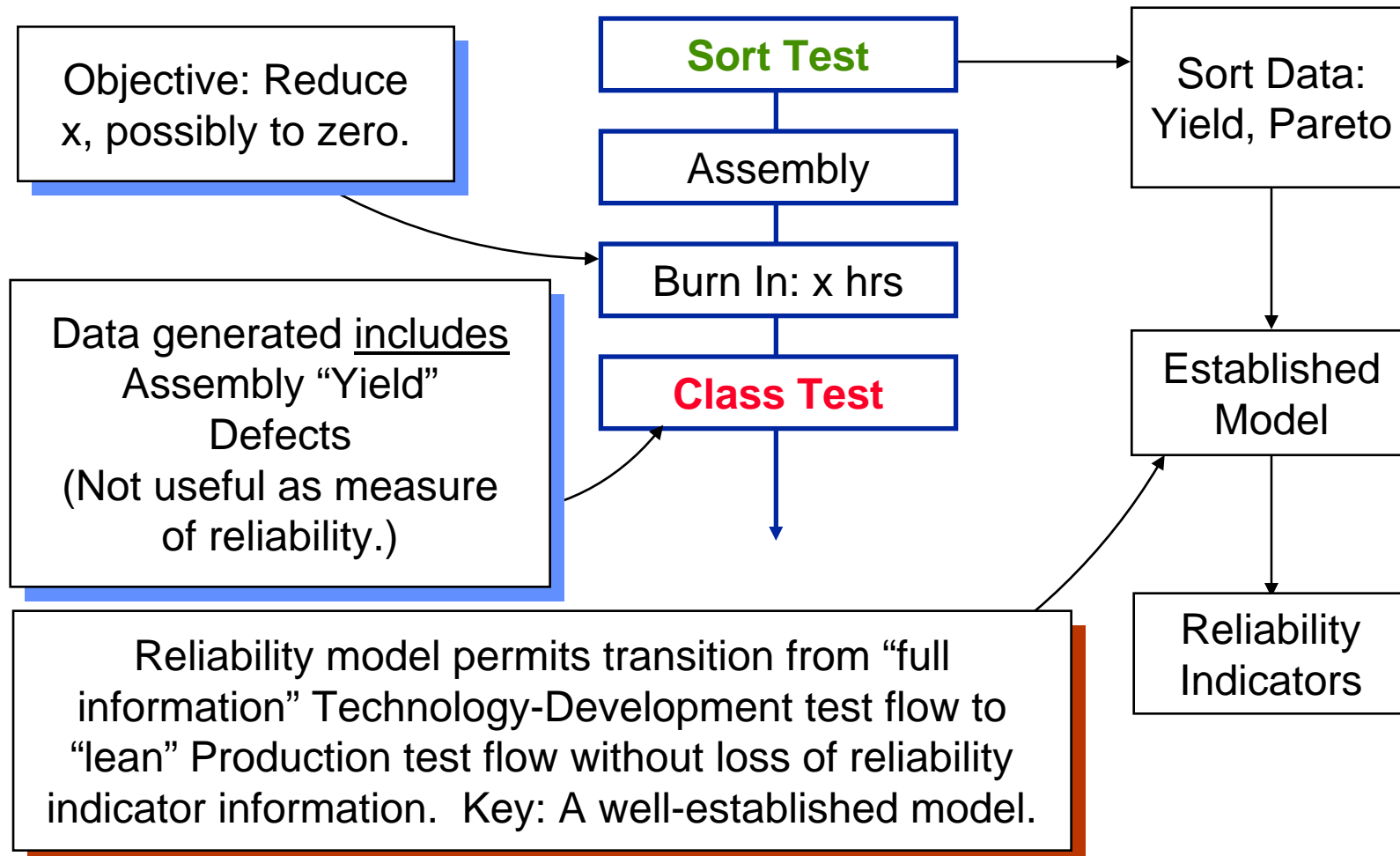
- so the probability of surviving t at T_2 and V_2 , *given that a unit has survived burn in* is :

$$S'^P(2|t) = \frac{\tilde{S}^P}{S^P(B|t_B)} = \prod_i \left[\frac{S_i^r \{1| AF_i(2|1)t + AF_i(B|1)t_B\}}{S_i^r \{1| AF_i(B|1)t_B\}} \right]^{R_i(p|r)}$$

Technology Development Test Flows



Production Test Flows



Test Programs

- Sort test is a wafer-level room temperature test.
- Class test is a unit level test using temperature-controlled hander.
- Sort and Class tests can stress units, particularly the high-voltage test.
 - Nominal temperature/volts is done last.
 - The stress in the test must be taken account of in low voltage burn-in (for acceleration studies).

Typical Sort Test

Temperatures:

Room

Voltages:

Low

High

Typical Class Test

Temperatures:

Hot: 90 C

Cold: -10 C

Room

Voltages:

Low

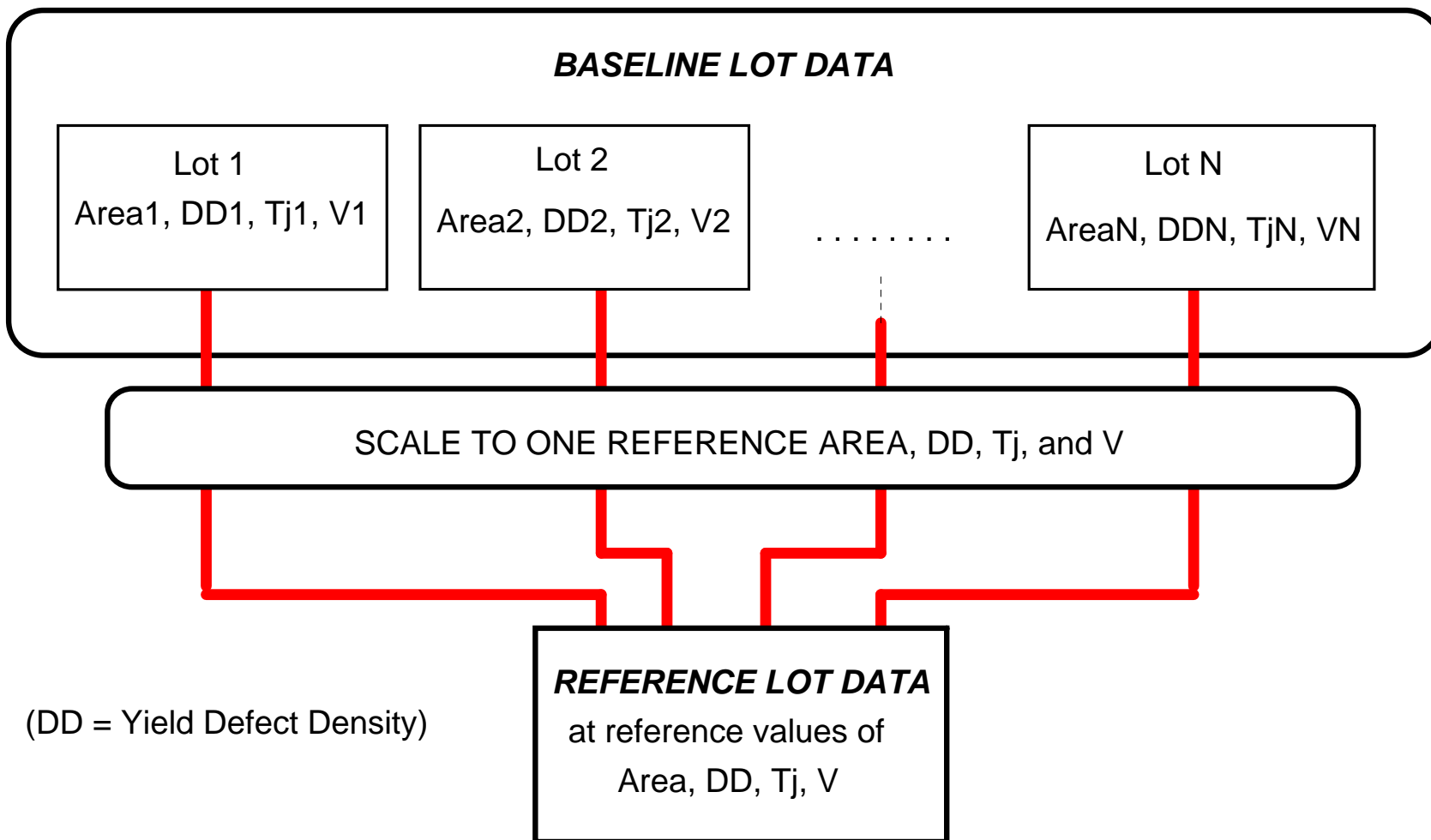
High

Nominal

Analysis of Reliability Data

- How do we get the “reference” survival function?
- Production burn-in data and extended life test data from a variety of products fabricated using a specific process are accumulated. This body of data is the “baseline lot” reliability data.
- Baseline data is consolidated using “known” acceleration models and defect scaling to produce a “reference lot” reliability data.
- Reference lot data is calculated at single reference values of defect density, die area, temperature and bias.
- Parametric fits to reference lot data gives “reference model distributions”.

Analysis of Reliability Data



Typical Minimum Data Requirements for Determination of Process Reference Models

- 4 lots of SRAM, 4000 units at $V = 140\%$ of nominal, and 125C.
- Several lots at other bias/voltage conditions to determine acceleration parameters.
 - nominal bias, room temperature
 - sometimes assign Q , C based on “known” mechanism.
- All lots Class tested before burn-in (“clean burn-in”)
- Readouts at 6, 48, 168, 500, 1000, 2000 hours.
- Known Yield and Defect Pareto for each lot.
- All failures validated, all failure signatures traceable to a physically analyzed failure.
 - “A Q and a C for every failure”.

Analysis of Reliability Data

- Example of one lot of *Baseline Lot Data*.

| Hours | 6 | 12 | 24 | 48 | 168 | 500 | 1k | 2k |
|-------------------|---|----|------|------|------|------|------|------|
| Pass Defect (PD) | - | - | 1 | 0 | 0 | 0 | 0 | 1 |
| Fab Defect (FD) | - | - | 3 | 0 | 0 | 2 | 0 | 0 |
| Bake Recov. (BR) | - | - | 0 | 0 | 0 | 0 | 0 | 0 |
| Junct. Spike (JS) | - | - | 0 | 0 | 0 | 0 | 0 | 0 |
| Sample Size (SS) | - | - | 2748 | 2744 | 2743 | 2293 | 2290 | 2290 |

| Mechanism | Q_i (eV) | C_i (1/volts) |
|-----------|------------|-----------------|
| PD | 0.3 | 1.8 |
| FD | 0.5 | 2.0 |
| BR | 1.0 | 0.0 |
| JS | 1.0 | 0.6 |

SRAM at $V = 5.5$ volt and $T_j = 131^\circ\text{C}$, die area = 36160 mils²,
 $D_{\text{yield}} = 1$ (arbitrary units)

Note: Model predictions and data in this tutorial are examples only and are not representative of Intel products.

Analysis of Reliability Data

- Example of *Reference Lot Data* combined from from multiple lots of various products fabricated using the process.

| Hours | 6 | 12 | 24 | 48 | 168 | 500 | 1k | 2k |
|--------|-------|------|-------|-------|-------|------|-------|------|
| PD | 0 | 0 | 1.6 | 0 | 0 | 0 | 3.2 | 6.2 |
| SS /PD | 22642 | 1609 | 38305 | 51551 | 45212 | 5480 | 11808 | 5297 |
| FD | 105.7 | 0 | 18.6 | 54.0 | 53.9 | 19.1 | 24.8 | 20.4 |
| SS /FD | 21056 | 1407 | 34973 | 48604 | 42288 | 4304 | 10409 | 4207 |
| BR | 0 | 0 | 7.3 | 4.6 | 0 | 0 | 7.7 | 0 |
| SS /BR | 18281 | 1059 | 29629 | 47932 | 39302 | 3798 | 9383 | 3632 |
| JS | 0 | 0 | 2.9 | 0 | 27.7 | 7.5 | 0 | 9.6 |
| SS/JS | 18281 | 1059 | 29155 | 45472 | 37964 | 3015 | 8616 | 2958 |

Scaled to a Reference Condition of
 $V = 7$ volts, $T_j = 160$ C, Area = 268,686
 mils²,
 $D_{\text{yield}} = 0.21$ (arbitrary units).

Analysis of Reliability Data

REFERENCE LOT DATA
at reference values of
Area, Defect Density, Tj, V

Hazard Analysis using Kaplan-Meier-Greenwood Algorithm

Fit Lognormal Distributions to Best Estimate and x% UCL KMG data points
x = 60%, 90%, 95%, 99%

REFERENCE MODEL DISTRIBUTIONS
Model Parameters for Each Mechanism
at reference values of
Area, Defect Density, Tj, V

Statistical Interlude: Hazard Analysis

- Data produced by burn-in and life-test flows is nearly always censored (has removals).
 - Because material is diverted into other stresses in TD.
 - Because failures are often invalidated.
 - Because of multiple failure mechanisms.
- A simple method of analysis. For each mechanism:
 - Calculate instantaneous hazard.
 - Find cumulative hazard.
 - Use $F = 1 - \exp(-H)$ to find cumulative failures.
 - Plot F vs time on log probability plot.

Statistical Interlude: Hazard Analysis

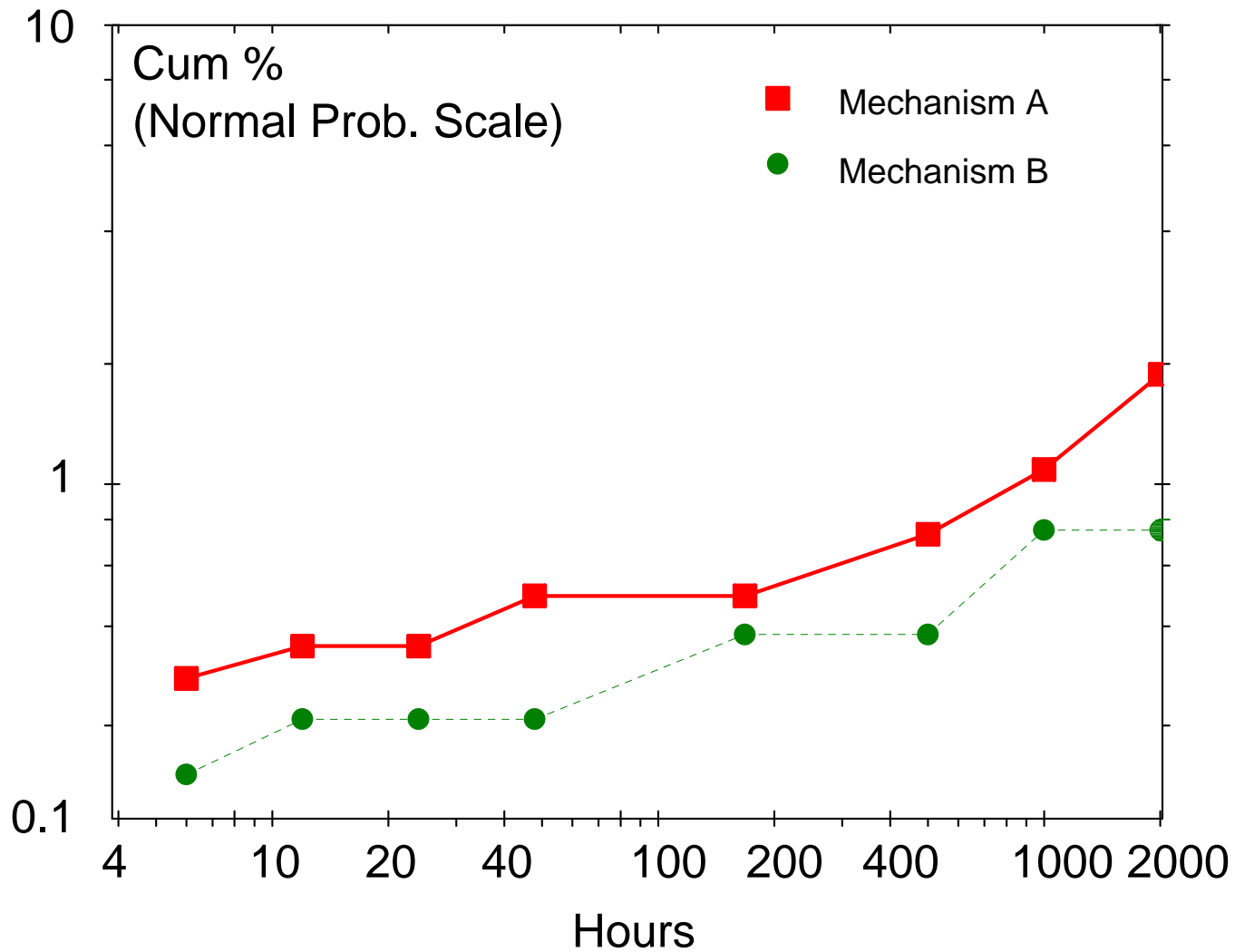
Two mechanisms with removals.

Removals: 0 0 1 839 150 149 147

| <i>Hours</i> | <i>6</i> | <i>12</i> | <i>24</i> | <i>48</i> | <i>168</i> | <i>500</i> | <i>1000</i> | <i>2000</i> |
|---|----------------------|----------------------|----------------------|----------------------|----------------------|----------------------|----------------------|----------------------|
| SS | 1423 | 1417 | 1415 | 1414 | 573 | 422 | 272 | 123 |
| N(A) | 4 | 1 | 0 | 2 | 0 | 1 | 1 | 1 |
| N(B) | 2 | 1 | 0 | 0 | 1 | 0 | 1 | 0 |
| $h_i(A)=N(A)/SS$ | 0.0028 | 0.0007 | 0.0000 | 0.0014 | 0.0000 | 0.0024 | 0.0037 | 0.0081 |
| $H_i(A)=\sum h_i(A)$ | 0.0028 | 0.0035 | 0.0035 | 0.0049 | 0.0049 | 0.0073 | 0.0110 | 0.0191 |
| <i>A: $F_i=1-exp(-H_i)$</i> | <i>0.0028</i> | <i>0.0035</i> | <i>0.0035</i> | <i>0.0049</i> | <i>0.0049</i> | <i>0.0073</i> | <i>0.0109</i> | <i>0.0189</i> |
| $h_i(B)=N(B)/SS$ | 0.0014 | 0.0007 | 0.0000 | 0.0000 | 0.0017 | 0.0000 | 0.0037 | 0.0000 |
| $H_i(B)=\sum h_i(B)$ | 0.0014 | 0.0021 | 0.0021 | 0.0021 | 0.0038 | 0.0038 | 0.0075 | 0.0075 |
| <i>B: $F_i=1-exp(-H_i)$</i> | <i>0.0014</i> | <i>0.0021</i> | <i>0.0021</i> | <i>0.0021</i> | <i>0.0038</i> | <i>0.0038</i> | <i>0.0075</i> | <i>0.0075</i> |

Plot cumulative failures (bold italics) on probability plot...

Statistical Interlude: Hazard Analysis



Analysis of Reliability Data

- The Kaplan-Meier-Greenwood (KMG) method handles censored readout data *and provides confidence intervals*. See Nelson*.
- Plot, lognormally, KMG estimates of cum fails.
- Least-squares fit of straight line through KMG plot points provides statistical model parameters.

Inverse Normal
Probability Function

$$y_i = \Phi^{-1}(F_i); \quad x_i = \ln(t_i)$$

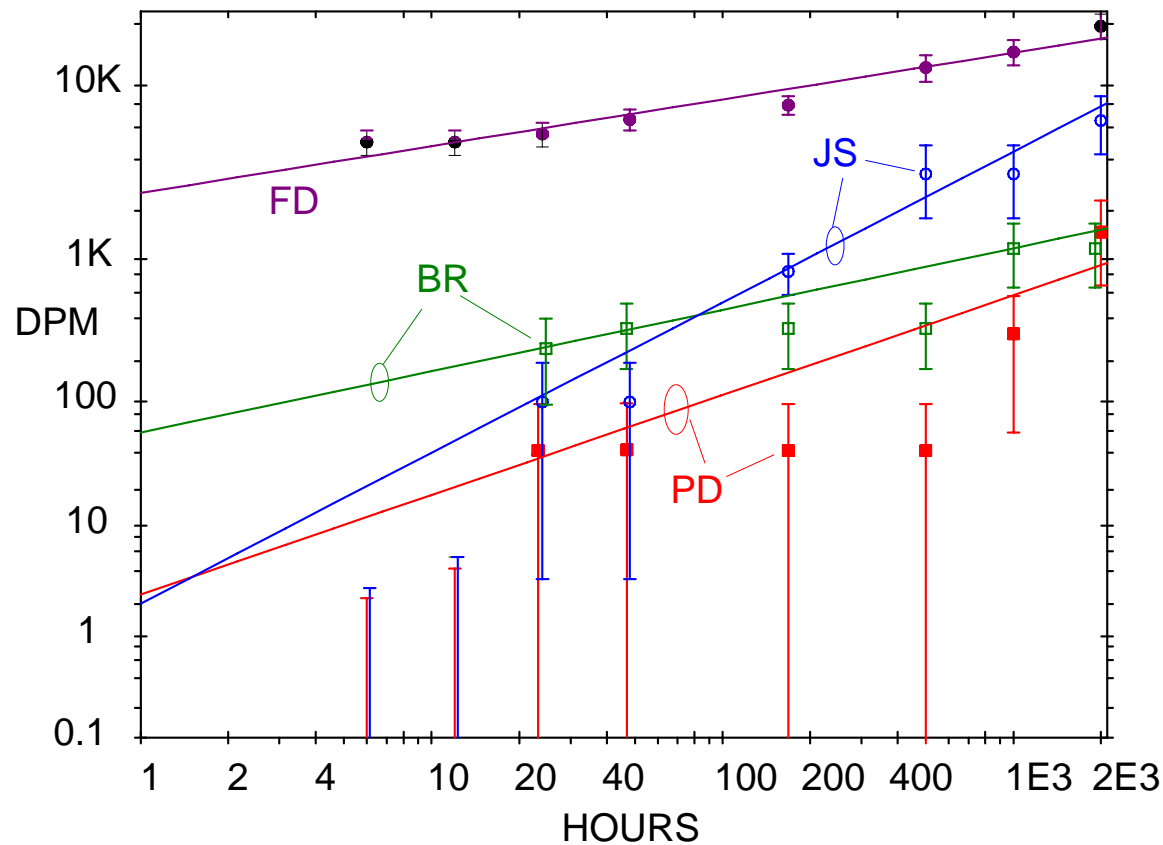
$$\sigma = 1 / \text{slope}; \quad \mu = -\sigma \times \text{intercept}$$

$$t_{50} = \exp(\mu)$$

* W. Nelson, "Accelerated Testing," John Wiley & Sons (1989), pp 145-151.

Analysis of Reliability Data

Reference Lot Data at $V = 7\text{ V}$, $T_j = 160\text{C}$, $A = 268,686\text{ mils}^2$,
 $D_{\text{yield}} = 0.21$ (arb. units). Plotted using KMG algorithm, and fitted to lognormal
time to failure distributions.



Analysis of Reliability Data

- Fitted lines through Best Estimate and the (one-sided) 95% Upper Confidence Limits for each mechanism gives...

| Mechanism | σ | μ Best Est. | μ 60% UCL | μ 90% UCL | μ 95% UCL | μ 99% UCL |
|-----------|----------|-----------------------|---------------------|---------------------|---------------------|---------------------|
| PD | 5.24 | 23.94 | 23.76 | 23.20 | 23.05 | 22.79 |
| FD | 11.20 | 31.33 | 31.24 | 30.90 | 30.78 | 30.57 |
| BR | 8.51 | 32.81 | 32.63 | 32.00 | 31.81 | 31.49 |
| JS | 3.47 | 16.00 | 15.92 | 15.65 | 15.58 | 15.44 |

At reference condition: $V = 7 \text{ V}$, $T = 160\text{C}$, $A = 268686 \text{ mil}^2$,
 $D_{\text{yield}} = 0.21$ (arbitrary units)
 (The reference condition *must* be specified.)

Analysis of Reliability Data

- Substitution of parameters into the lognormal distribution gives the “reference” survival function at time t in environmental condition “2” for the process:

$$S_i^r(2|t) = 1 - \Phi\left(\frac{\ln[AF_i(2|1)t] - \mu_i}{\sigma_i}\right)$$

where μ and σ for the mechanism are known at the reference condition “1”.

- This would be substituted, for example, into

$$S^p(2|t) = \prod_i [S_i^r\{1|AF_i(2|1)t\}]^{R_i(p|r)} \quad R_i(p|r) = \frac{P^p(i) \times \ln(Y^p)}{P^r(i) \times \ln(Y^r)}$$

Statistical Interlude: Weibull Analysis

- The reference model can also be fitted to a set of Weibull distributions
 - Characteristic life: α ; Shape; β for each mechanism
- Weibull distributions have convenient mathematical properties:

$$W(t, \alpha, \beta) \equiv \exp\left[-\left(\frac{t}{\alpha}\right)^\beta\right]$$

$$[W(t, \alpha, \beta)]^n = W\left(t, \frac{\alpha}{n^{1/\beta}}, \beta\right)$$

Statistical Interlude: Weibull Analysis

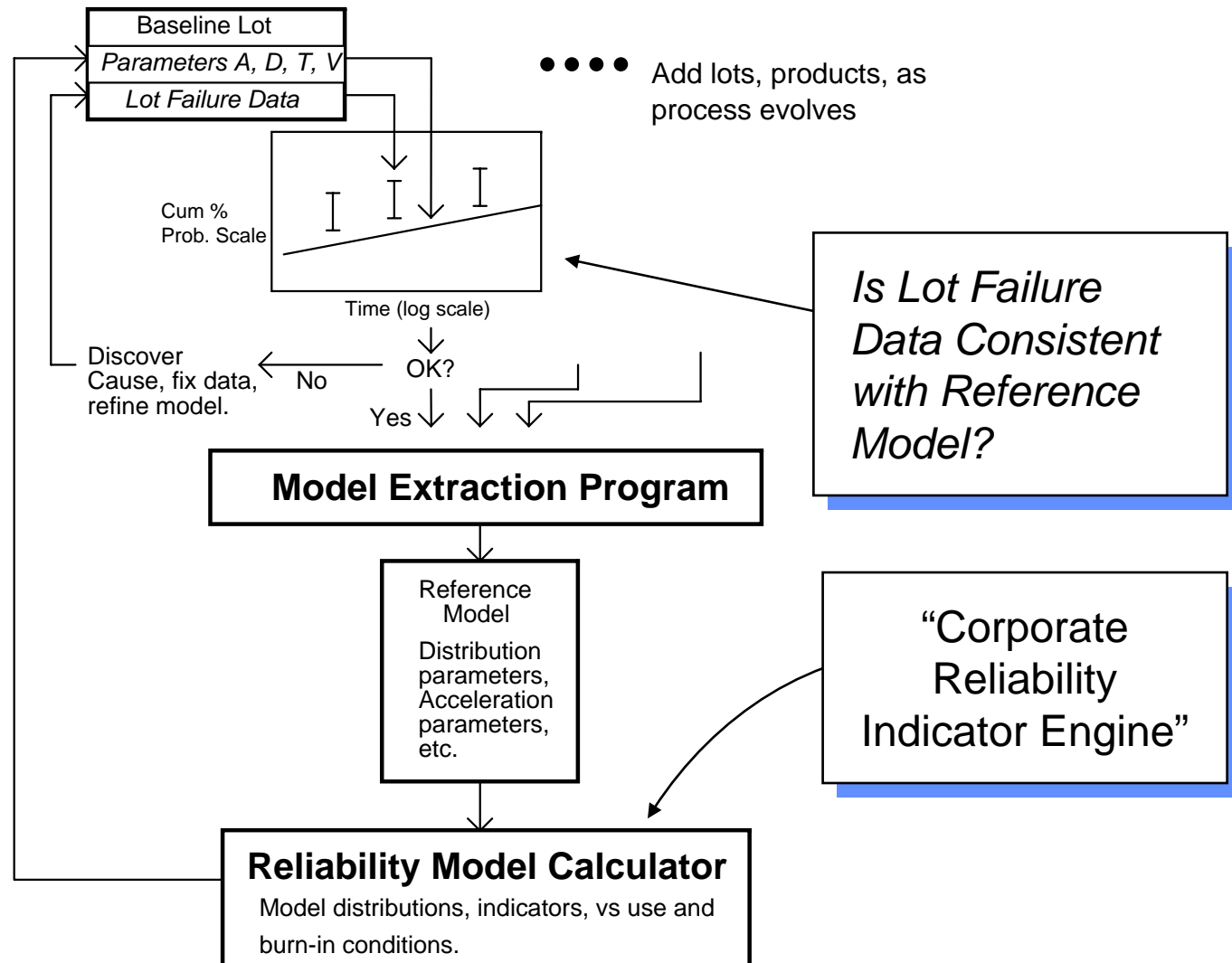
- For example, the product survival function without burn, and for an invariant Pareto, becomes:

$$S^p(2|t) = \prod_i W \left(AF_i(2|1)t, \frac{\alpha_i}{\left(\frac{\ln Y^p}{\ln Y^r} \right)^{1/\beta_i}}, \beta_i \right)$$

Each mechanism has a scaled characteristic life...

...but the same shape parameter as the reference product.

Determining Process Reference Model



Refinement of Process Reference Models

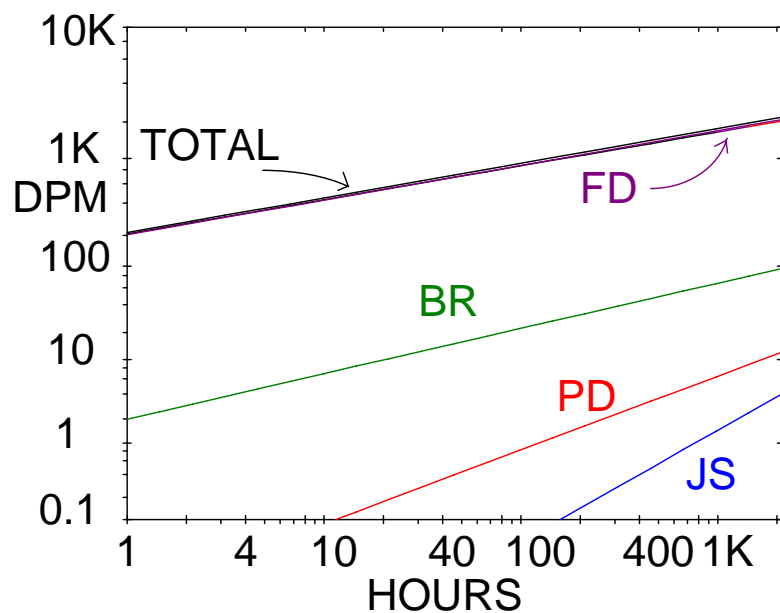
- Add *product* lots to baseline lot set.
 - Reveal mechanisms missed by SRAM model.
- Check for consistency with reference model.
 - Some lots class tested at a single-point (6 hr, 125C, 140%V), full F/A, known lot iso, at a minimum.
 - If failure rates are higher than predicted by model, a “red flag” is indicated.
- Refine the reference model
 - Re-extract using Model Extraction Software.
 - Re-extract and install model
 - » Immediately if change is significant.
 - » On annual cycle if product is consistent with model.

Reliability Prediction

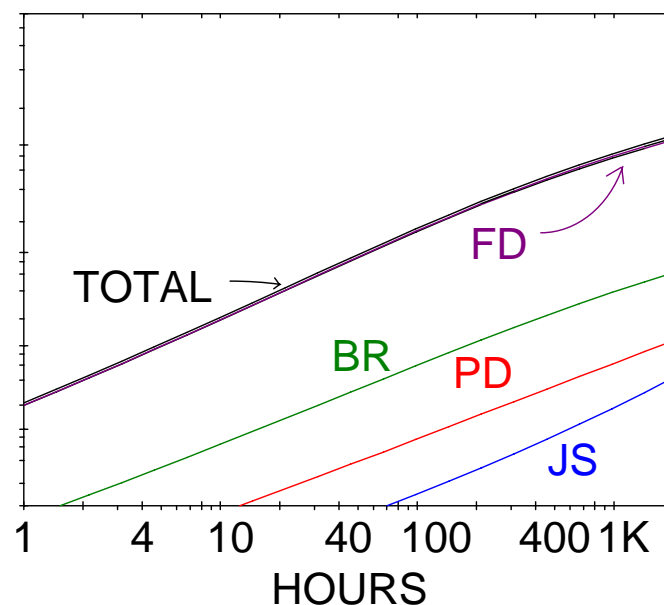
- Effect of burn in on SRAM reliability.
- Model predictions vs individual lot data from baseline data set.
- Calculation of standard reliability indicators.

Reliability Prediction

- Example: Predicted fallout and effect of burn-in for SRAM (Area = 36160 mil², $D_{\text{yield}} = 1$, $V = 5$ volts, $T_j = 85\text{C}$)



No Burn-In



After 10 hours 125C, 5.5 volt burn-in

Reliability Prediction

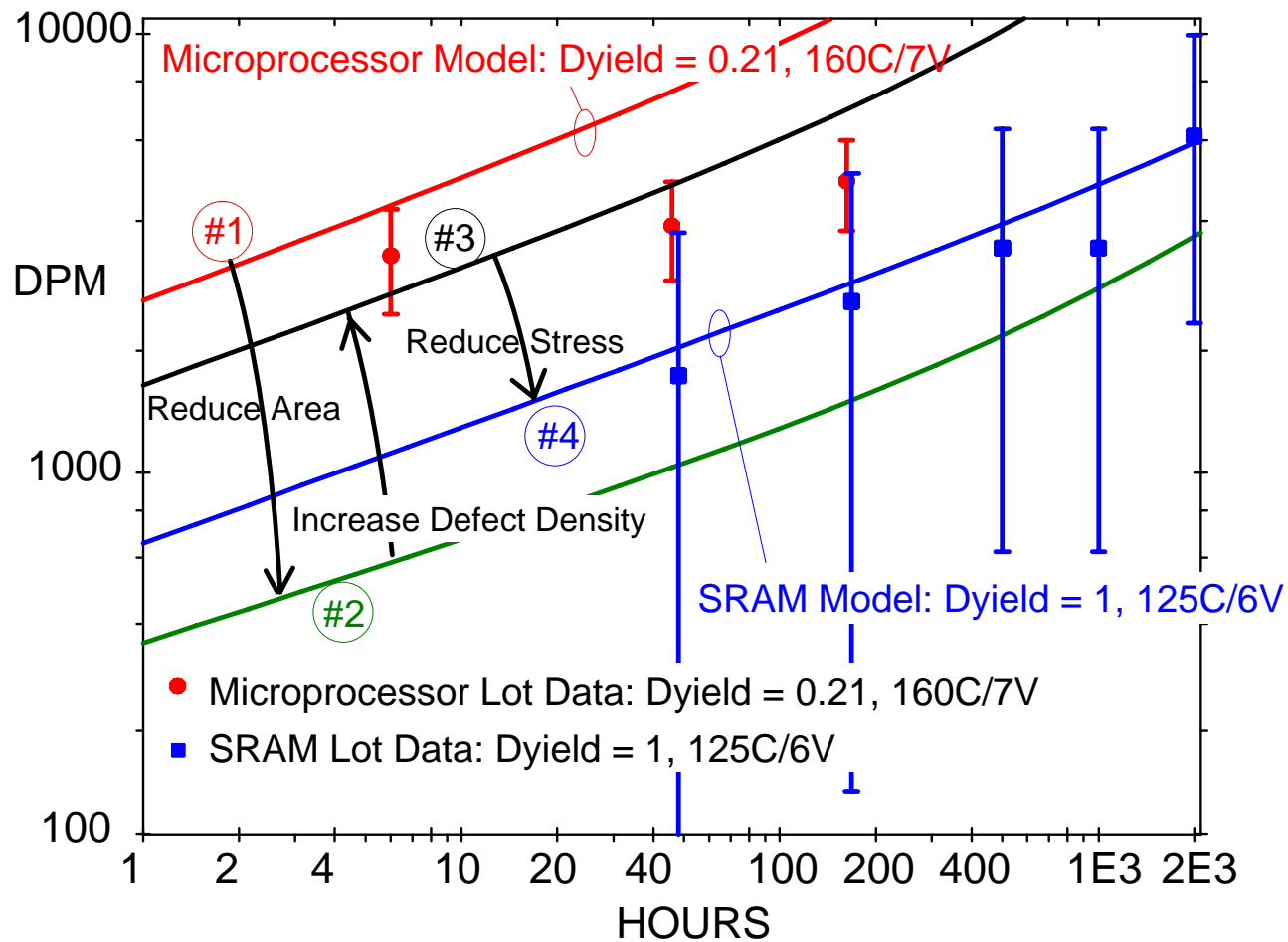
- Model predictions of the reference model based on the entire baseline lot data set *versus* individual data sets selected from the baseline data set.
- A sequence of conditions ranging from conditions of microprocessor data for a particular lot to conditions of SRAM data for a particular lot...

| No. | A(mil ²) | Dyld | T(C) | V(volts) | |
|-----|----------------------|------|------|----------|-------------------------|
| 1 | 268,686 | 0.21 | 160 | 7 | Microprocessor lot data |
| 2 | 36,160 | 0.21 | 160 | 7 | |
| 3 | 36,160 | 1.00 | 160 | 7 | |
| 4 | 36,160 | 1.00 | 125 | 6 | SRAM lot data |

Note: Model predictions and data are examples only and are not representative of Intel products.

Reliability Prediction

Model Predictions of Total Failures vs Baseline Lot Data



Reliability Prediction

- Standard reliability indicators

- Infant Mortality: 0-100 hours at 85C and 5V (DPM)

$$10^6 \times \{1 - S'(t = 100 \text{ hours})\}$$

- Early Life Mortality: 0 - 1 year at 85C and 5V (DPM)

$$10^6 \times \{1 - S'(t = 8760 \text{ hours})\}$$

- Early Life Average Failure Rate (AFR): 0-1 year AFR at 85C and 5V (Fits)

$$-10^9 \times \ln[S'(t = 8760 \text{ hours})] / 8760$$

- Long Term AFR: 1-10 year AFR at 85C and 5V (Fits)

$$10^9 \times \{\ln[S'(t = 8760 \text{ hours})] - \ln[S'(t = 87600 \text{ hours})]\} / 78840$$

Note: Prime indicates “burned-in” survival function.

Reliability Prediction

Reliability Indicators for microprocessor example at $T_j = 85\text{C}$ and $V = 5$ volts, $D_{yield} = 0.21$, Area = 268,686 mil²

| Mech. | CUM FAIL | | AFR | | |
|-------------------------------|---------------|--------------|--------------|---------------|----|
| | 0-100h DPM | 0-1yr DPM | 0-1yr FIT | 1-10yr FIT | |
| No Burn-In | PD | 2 | 69 | 8 | 4 |
| | FD | 1406 | 4827 | 552 | 48 |
| | BR | 39 | 305 | 35 | 6 |
| | JS | 0 | 42 | 5 | 6 |
| | Total | 1447 | 5241 | 600 | 65 |
| Burn-In: 168 hr at 160C/7V | PD | 0.4 | 35 | 4 | 3 |
| | FD | 1.6 | 133 | 15 | 13 |
| | BR | 0.5 | 45 | 5 | 4 |
| | JS | 0.6 | 52 | 6 | 6 |
| | Total | 3.1 | 266 | 30 | 25 |

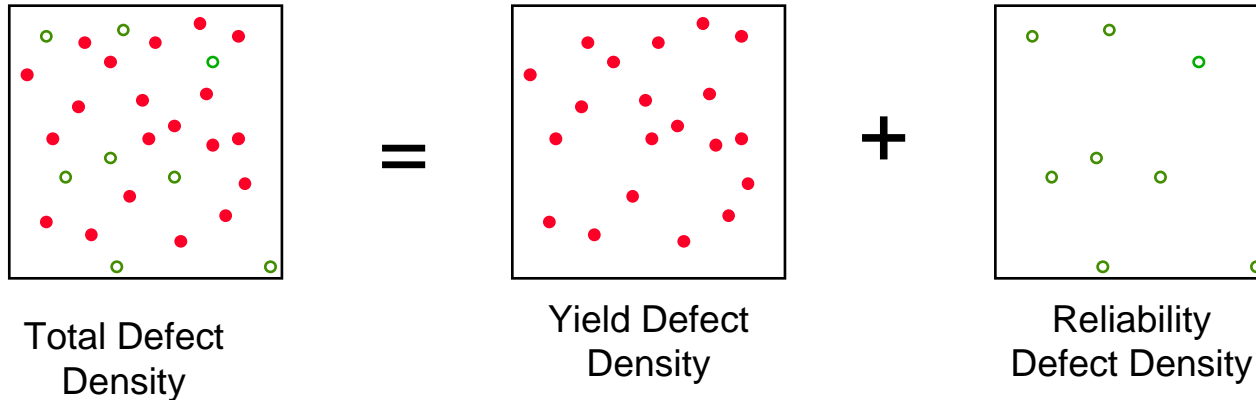
Benefits

- Estimation of the reliability characteristics of any product, including the contributions of various mechanisms.
- Estimation of failure rates of complex products without full reliance on failure analysis, or complete data.
- Estimation of the effect of die area, array area, etc. on the reliability characteristics of any proposed or new product using no, or minimal, data.
- Quantify the reliability benefits of process continuous improvement through defect density reduction.
- Calculate the effect of burn-in.
- Calculate reliability indicators useful to customers, at any desired level of confidence.

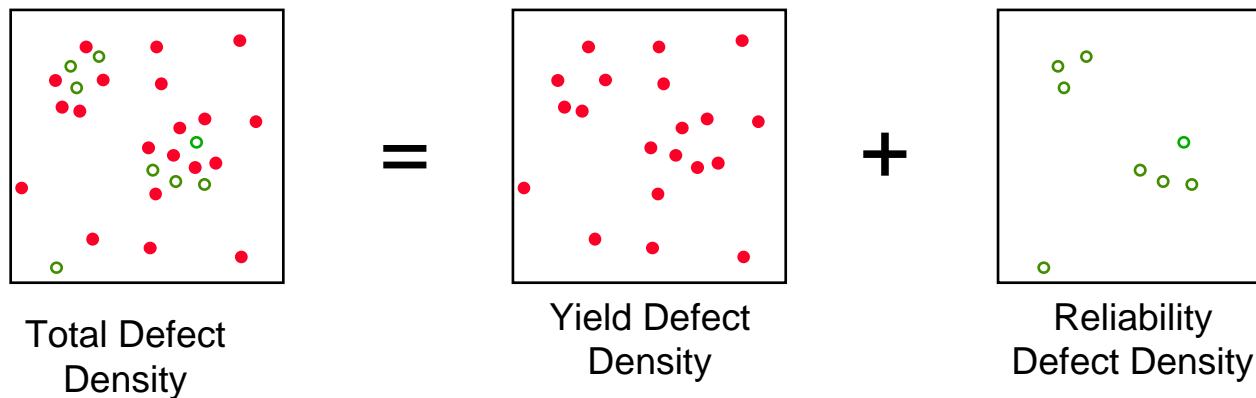
Supplementary Slides on Clustering Effects

Effects of Defect Clustering

- Random defects:



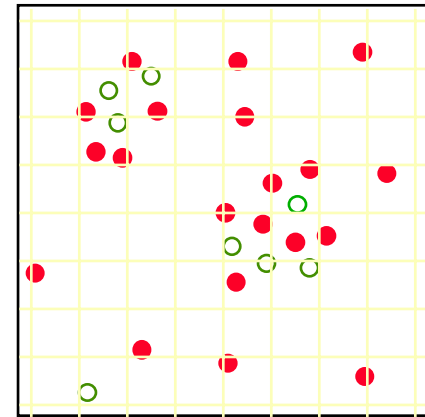
- Clustered defects:



Defect Density Variation

- Clustering can be modeled as a spatial variation of defect density.
- The clustering can be described by a gamma function distribution:

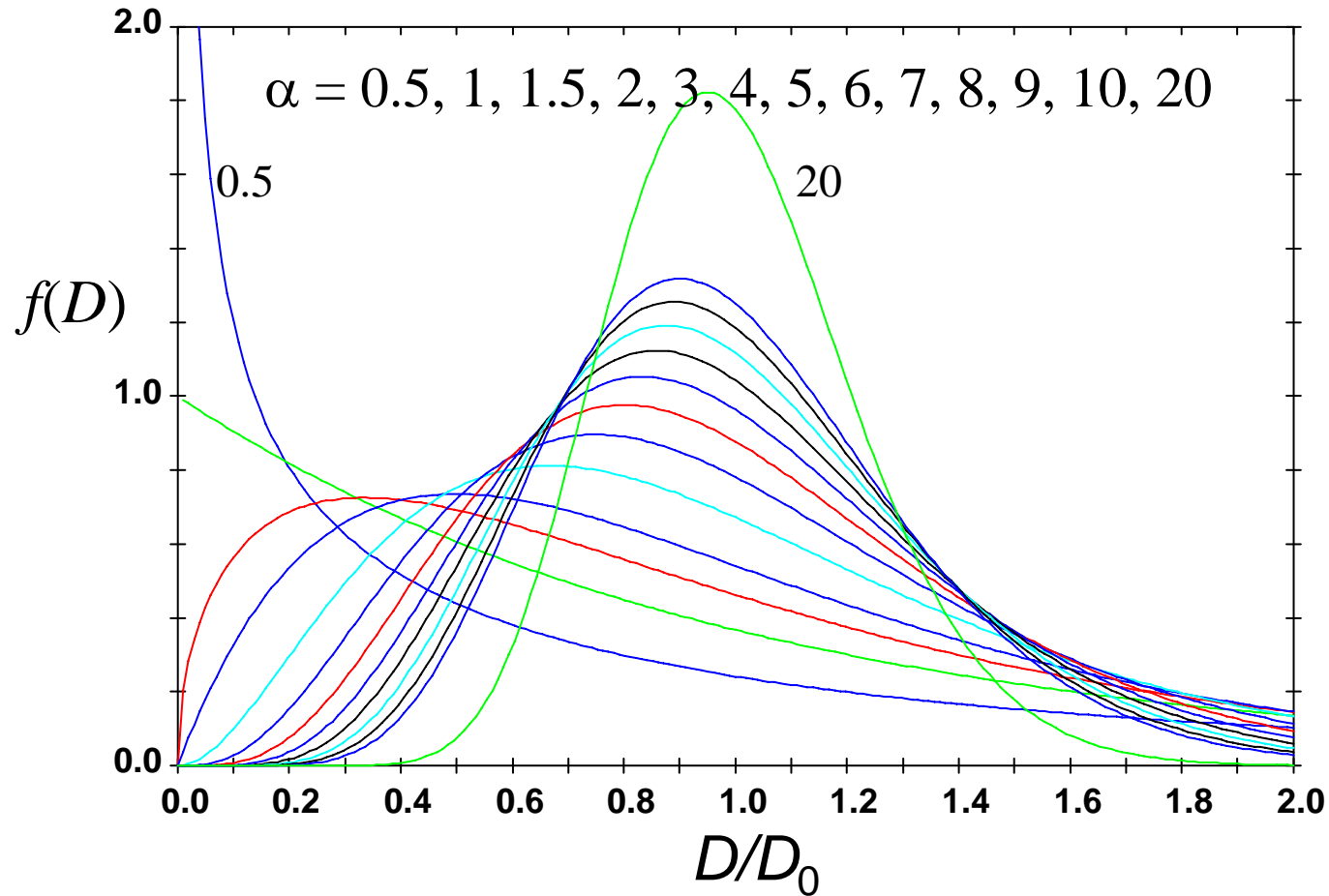
$$f(D) = \frac{\alpha}{D_0 \times \Gamma(\alpha)} \left(\alpha \frac{D}{D_0} \right)^{\alpha-1} \exp\left(-\alpha \frac{D}{D_0} \right)$$



- The spread in the defect density is described by $\alpha = \text{var}(D)/D_0^2$
- D_0 is the average defect density (defects/cm²)

Defect Density Variation

- The defect density distribution approaches a delta function as $\alpha \rightarrow \infty$.



Yield Function with Clustering

- The yield function is the probability of occurrence of one defect on a die of area A:

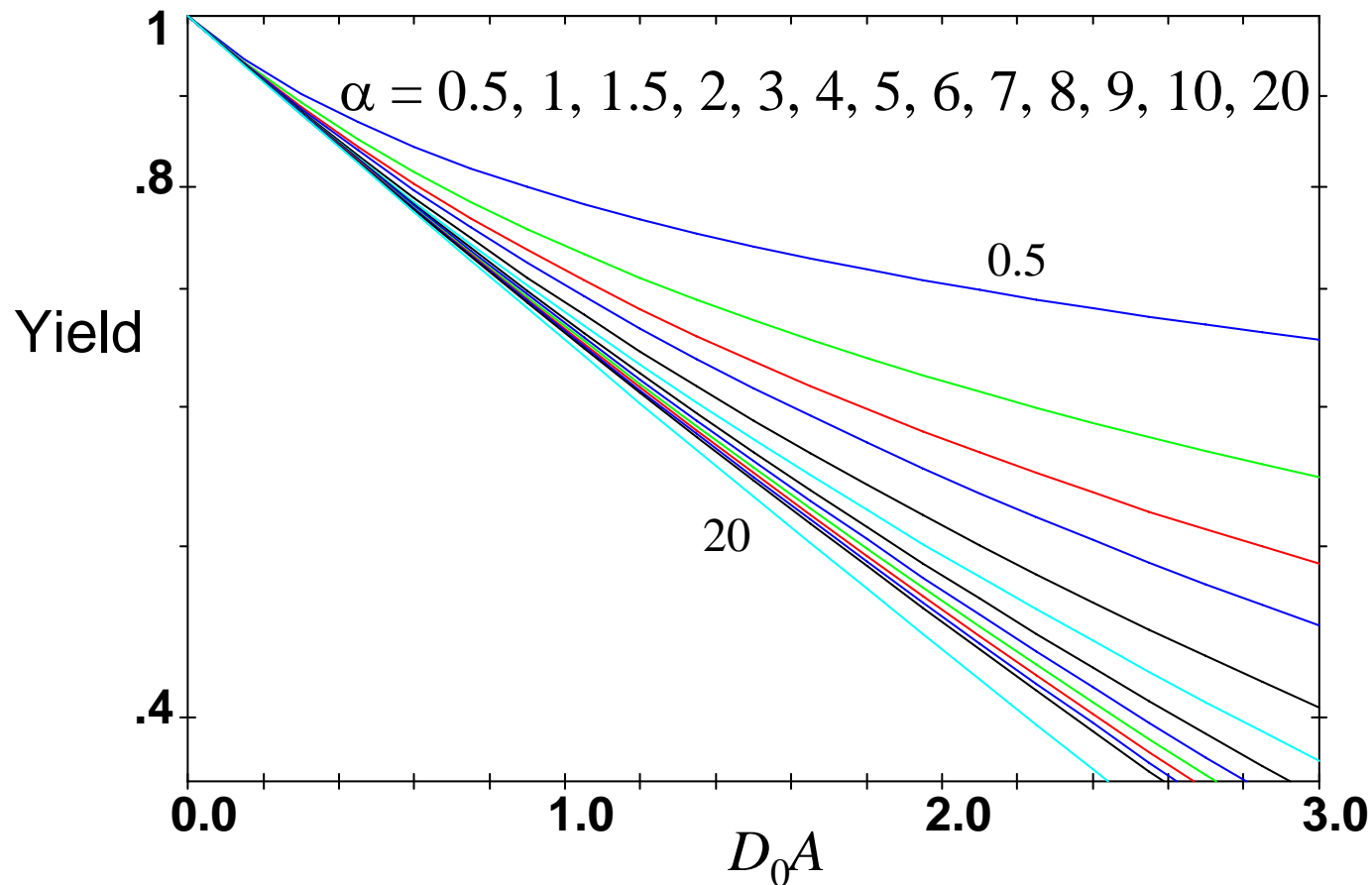
$$Y = \int_0^{\infty} \exp(-DA) f(D) dD = \frac{1}{\left(1 + \frac{D_0 A}{\alpha}\right)^{\alpha}}$$

- In the limit of no clustering (uniform D), this becomes

$$\frac{1}{\left(1 + \frac{D_0 A}{\alpha}\right)^{\alpha}} \xrightarrow{\alpha \rightarrow \infty} \exp(-D_0 A)$$

Yield Function with Clustering

- Clustering of defects gives higher yields than predicted by random defect model...



Clustering of Latent Reliability Defects

- How does the chip reliability survival function vary with non-uniform defect density?
- Define $s(t)$, the point defect survival function.
- For uniform defects the chip survival function is $S(t) = [s(t)]^{AD}$, where AD is the number of defects on the chip.
- If defects are clustered..

$$S(t) = \frac{1}{\left(1 - \frac{AD_0 \ln s(t)}{\alpha}\right)^\alpha}$$

Scaling of Survival Probability

- Consider
 - A product with *unknown* survival probability $S^p(t)$ and,
 - A reference test vehicle with *known* survival probability $S^r(t)$.
 - The defect density variation, α , is the same for both unknown product and reference test vehicle
 - The “scaling ratio” is, in terms of reliability defect density,

$$R_{\text{rel}}(p|r) = \frac{A^p D_{\text{rel } 0}^p}{A^r D_{\text{rel } 0}^r}$$

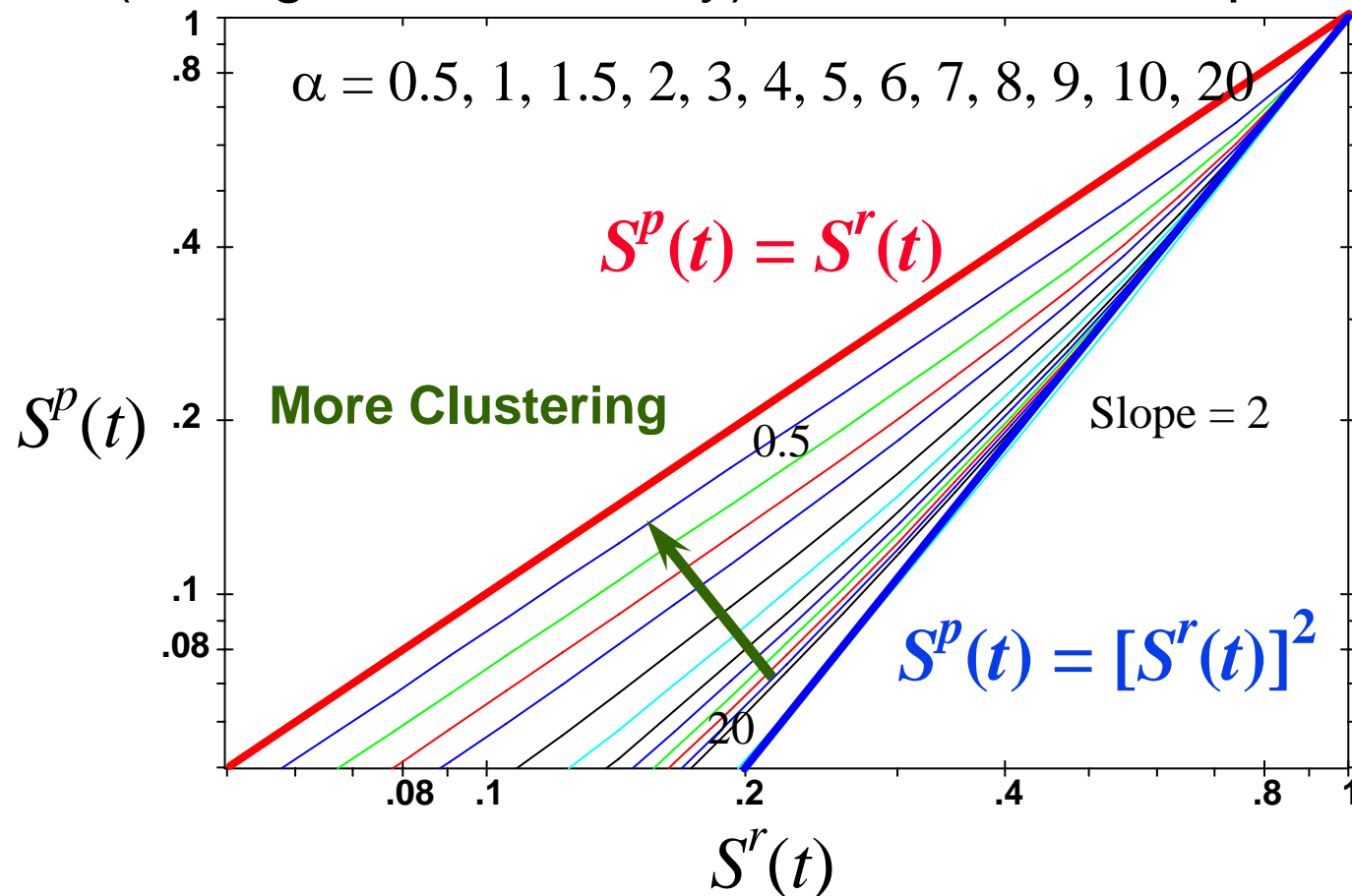
- So the unknown survival probability is

$$S^p(t) = \left\{ 1 + R_{\text{rel}}(p|r) \times \left([S^r(t)]^{\frac{1}{\alpha}} - 1 \right) \right\}^{-\alpha}$$

$$\xrightarrow{\alpha \rightarrow \infty} [S^r(t)]^{R(p|r)}$$

Survival Function Scaling

- For the case where product p has twice the area (or avg. defect density) of the reference product:



Yield-Reliability Relationship

- From the yield formulae

$$R_{\text{yield}}(p|r) = \frac{A^p D_{\text{yield } 0}^p}{A^r D_{\text{yield } 0}^r} = \frac{(Y^p)^{-\frac{1}{\alpha}} - 1}{(Y^r)^{-\frac{1}{\alpha}} - 1} \xrightarrow{\alpha \rightarrow \infty} \frac{\ln Y^p}{\ln Y^r}$$

- If we make the fundamental assumption

$$R_{\text{reliability}}(p|r) = \frac{A^p D_{\text{reliability } 0}^p}{A^r D_{\text{reliability } 0}^r} \cong \frac{A^p D_{\text{yield } 0}^p}{A^r D_{\text{yield } 0}^r} = R_{\text{yield}}(p|r)$$

- *And* assume the dispersion in reliability and yield defect densities are the same

$$\alpha = \alpha_{\text{reliability}} \cong \alpha_{\text{yield}}$$

Yield-Reliability Relationship

- Then we can calculate the product survival function from yield characteristics

$$S^P(t) = \left\{ 1 + \frac{(Y^P)^{-\frac{1}{\alpha}} - 1}{(Y^r)^{-\frac{1}{\alpha}} - 1} \times \left([S^r(t)]^{-\frac{1}{\alpha}} - 1 \right) \right\}^{-\alpha}$$

$$\xrightarrow{\alpha \rightarrow \infty} [S^r(t)]^{\frac{\ln Y^P}{\ln Y^r}}$$

For a given defect density, more clustering gives higher yield *and* higher reliability.

Extension to Multiple Mechanisms

$$\begin{aligned}
 S^P(t) &= \prod_i \left\{ 1 + \frac{(Y_i^P)^{-\frac{1}{\alpha_i}} - 1}{(Y_i^R)^{-\frac{1}{\alpha_i}} - 1} \times \left([S_i^R(t)]^{-\frac{1}{\alpha_i}} - 1 \right) \right\}^{-\alpha_i} \\
 &= \prod_i \left\{ 1 + \frac{P_i^P [(Y^P)^{-\frac{1}{\alpha}} - 1]}{P_i^R [(Y^R)^{-\frac{1}{\alpha}} - 1]} \times \left([S_i^R(t)]^{-\frac{1}{\alpha}} - 1 \right) \right\}^{-\alpha} \\
 &\xrightarrow{\alpha \rightarrow \infty} \left(\prod_i S_i^R(t)^{\frac{P_i^P}{P_i^R}} \right)^{\frac{\ln Y^P}{\ln Y^R}}
 \end{aligned}$$

Y^P and Y^R are the total yields (all mechanisms).

P_i^P and P_i^R are yield Paretos.

α is the defect density dispersion parameter (all mechanisms)